

# Power Delivery for Future Experiments

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Richard Sumner - *CMCAMAC LLC*



## Agenda

- ❖ Examples of systems running @ LHC
- ❖ Losses & Efficiency
- ❖ Is there a better way?
- ❖ 2D Inductors – Air Core / Coreless
- ❖ Radiation Tolerance / Testing / Noise
- ❖ Wide Band gap
- ❖ Notes on our Direction of our Work
- ❖ SiD (LCRD) Powering – It has paid rent to Yale
- ❖ Commercial Power World
- ❖ Toroid vs. 2D Inductor Noise Comparison
- ❖ Carbon Fiber for shielding
- ❖ Summary

# CMS ECAL Powering @ LHC Running Now

## CMS ECAL 2.5 v @ 50,000 AMPS

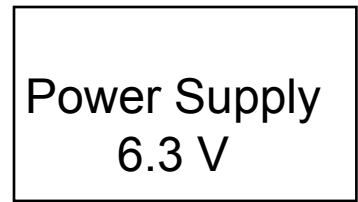
Power Supply output = 315 KW  
Power loss in Leads to SM = 100 KW  
Power loss in Regulator Card = 90 KW  
Power Delivered @ 2.5 V = 125 KW

# of Power Supplies ~ 700

# of ST LDO Chips = 35 K LHC Radiation Hard made by ST Microelectronics

# of LVR Cards = 3,100

**Yale: Designed, built, burn-in and Tested.**



64 Amps

30 m

Vdrop = 2V  
Pd = 128 W

50 mm<sup>2</sup> (AWG 00)

2x16 mm<sup>2</sup> (AWG 6)

1 to 3 m

SM: Super Module

4.3 V

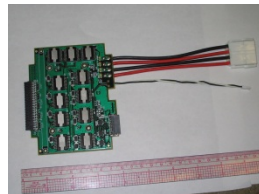
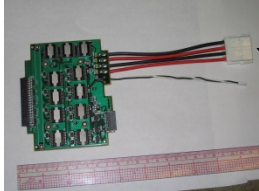
Junction Box

2.5V

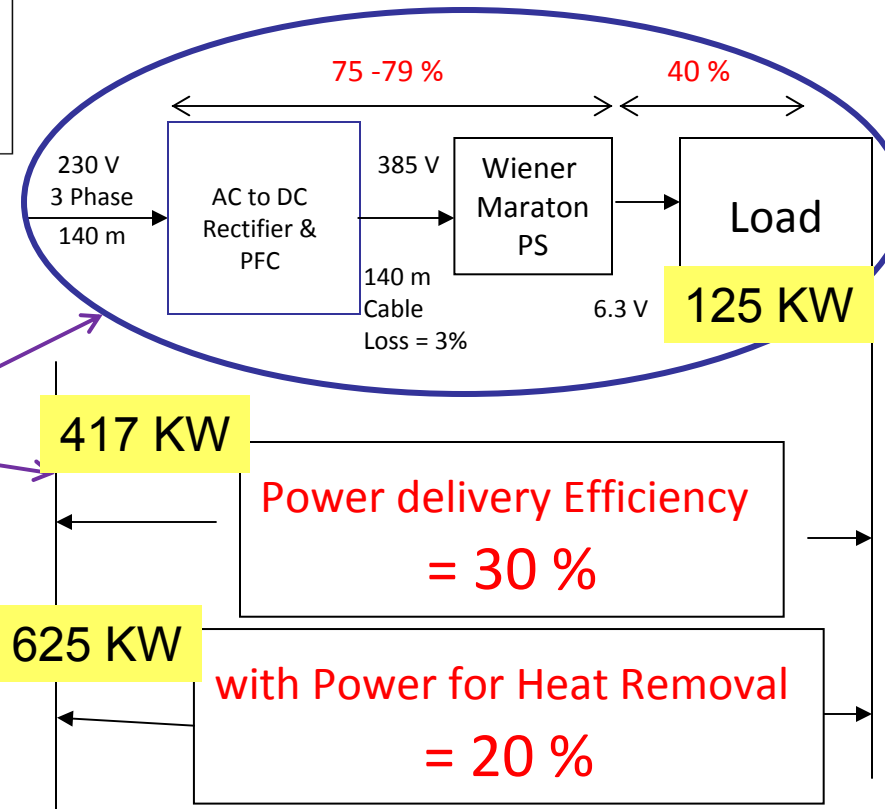
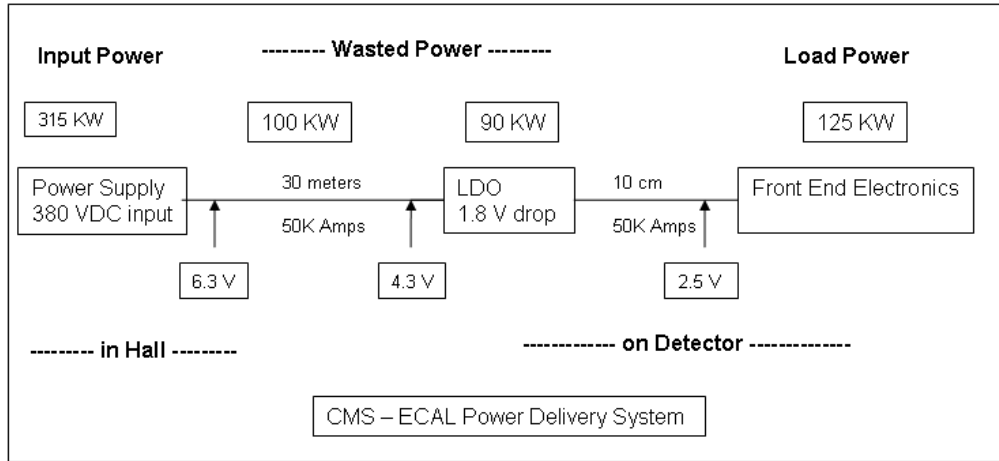
64 amps

160 W

4 LVR Boards



# Power Chain Efficiency for CMS ECAL



*Represents the efficiency of power delivery to a physics detector, e.g. ECal*

*It takes 2 watts of power to remove 1 watt of heat load*

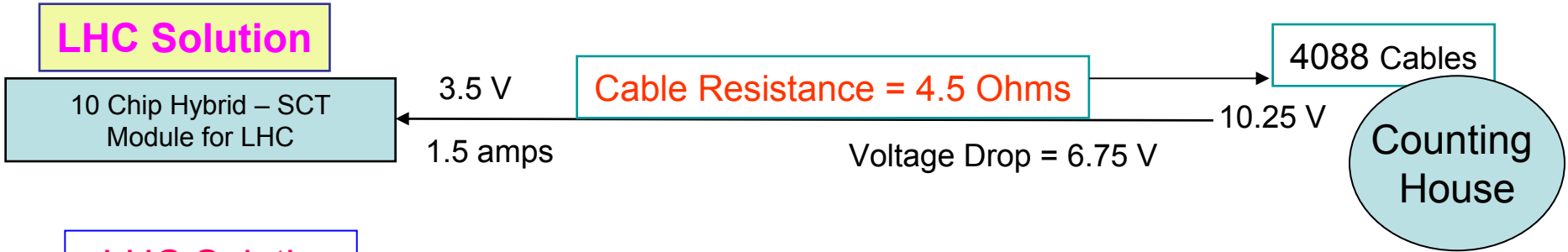


# Is there a better way to distribute power ?

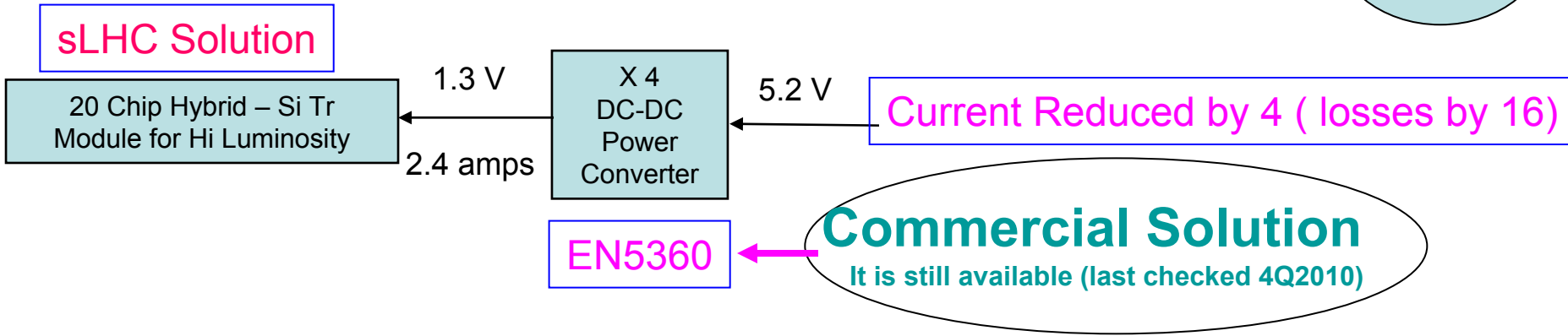
- Radiation & Magnetic fields depend on location of the sub-system
- High Radiation 1 Mrad -100 Mrads
- Magnetic Field Up to 4 T
- Load ~1 V Tens of Kilo- Amps
- Feed High Voltage and Convert - *like AC power transmission*
- Commercial Technologies – *No Custom ASIC Chips*
- Learn from Semiconductor Industry LDMOS, Thin Gate Oxide

Length of Power Cables = 140 Meters

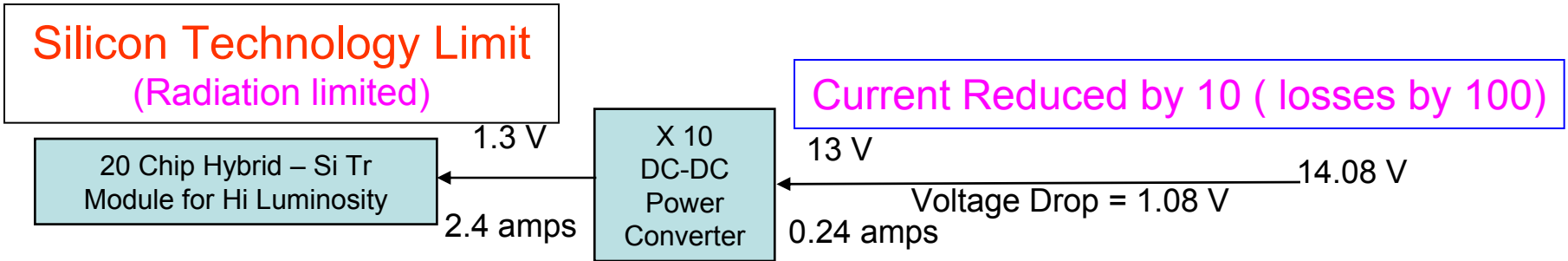
**LHC Solution**



**sLHC Solution**



**Silicon Technology Limit**  
(Radiation limited)



> X 40 with Gallium Nitride Transistors

## Why we need Air Core Inductor for Buck converters ?

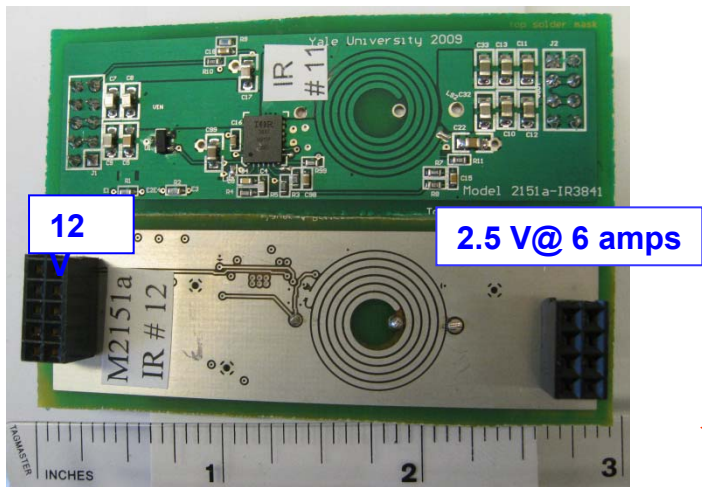
1. Run in 4 Tesla field. Any magnetic material in the field will move when magnet is turned on.
2. Some detectors exposed to radiation environments 1 -100 Mega Rads
3. Low mass: So interacting protons don't create secondary particle noise

1. Two spirals in close proximity - Magnetic field storage vs distance
2. How can we reduce leakage flux?
- 3.

This is for Coil Design engineers

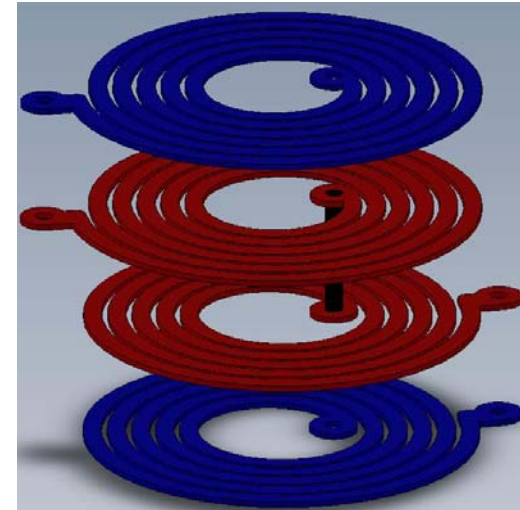
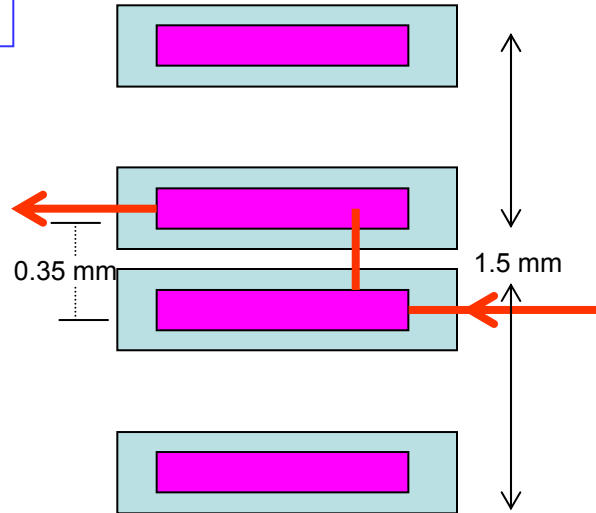
## Plug In Card with Shielded Buck Inductor

## Coupled Air Core Inductor Connected in Series

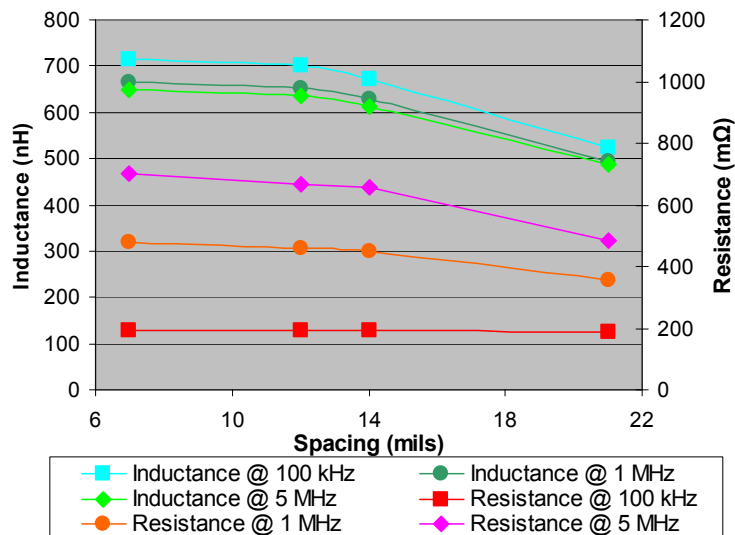


### Different Versions

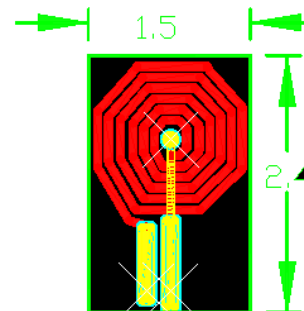
- ❖ Converter Chips , Max8654 monolithic IR8341 3 die MCM
- ❖ Coils Embedded 3oz cu, Solenoid 15 mΩ & Etched 0.25mm cu foil



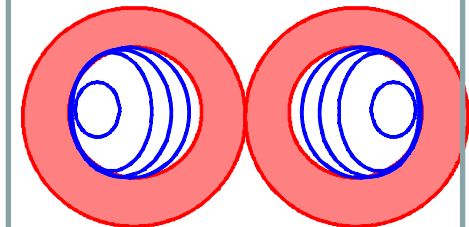
### Inductance and Resistance vs Coil Spacing



2 oz copper for coil on thin Laminate  
2 coils in series for larger L



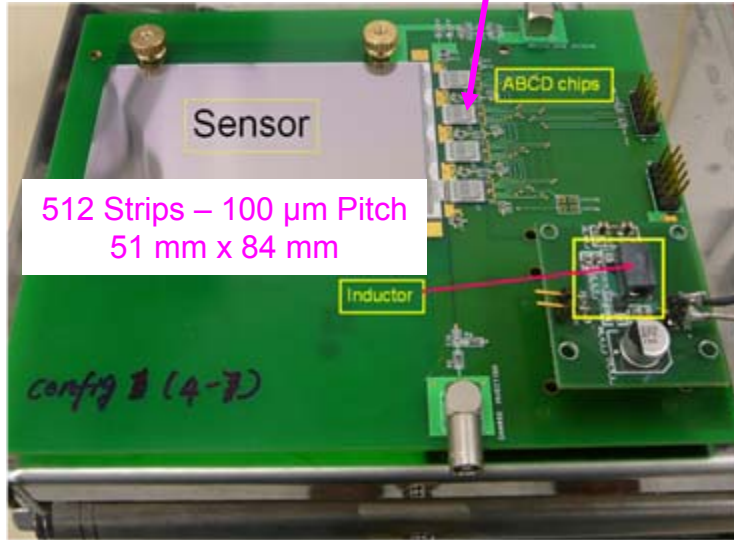
### Proximity Effect



Current Distribution in Neighboring Conductors

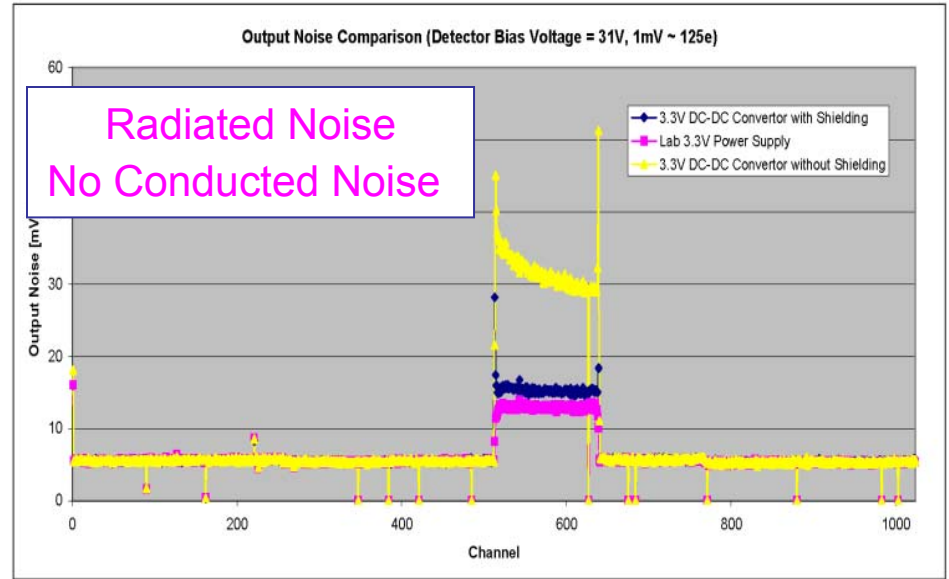
Test @ BNL

Only One Chip Bonded



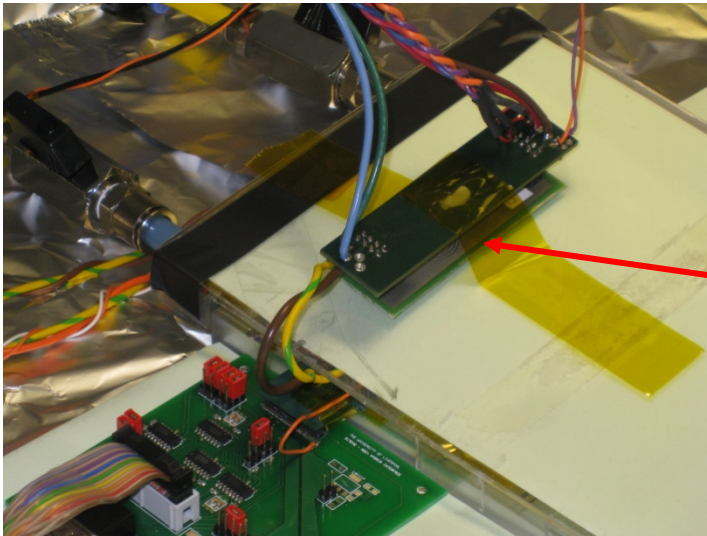
512 Strips – 100  $\mu$ m Pitch  
51 mm x 84 mm

# Noise Tests with Silicon Sensors



Radiated Noise  
No Conducted Noise

Test @ Liverpool in September 2009



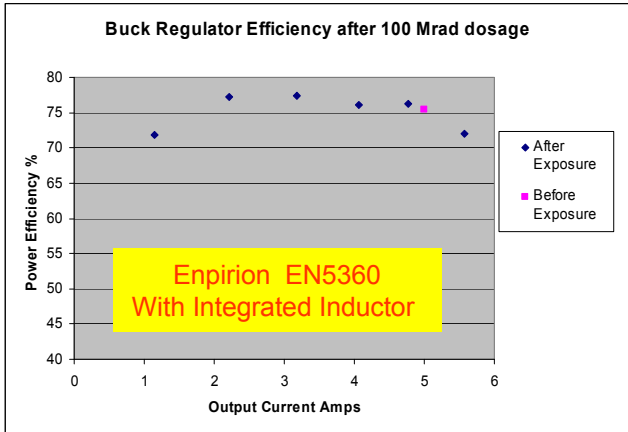
Plug in Card  
1 cm from Coil  
facing Sensor

20  $\mu$ m Al foil  
shielding

Coil Type	Analog Power to FE	Input Noise electrons rms
Solenoid	DC - DC	881
Solenoid	Linear	885
Spiral Coil	DC - DC	666
	Linear	664

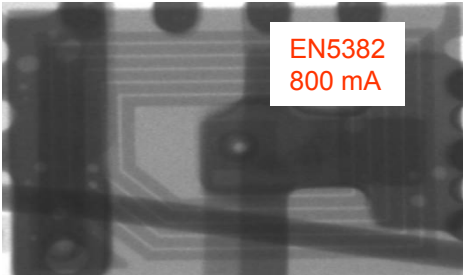
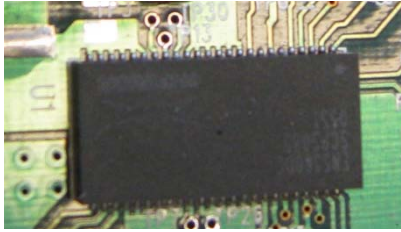


# DC-DC POWER CONVERTER INTEGRATION



Found out at Power Technology conference 0.25  $\mu$ m Lithography

- Irradiated Stopped on St. Valentines Day 2007
- We reported @ TWEPP 2008 - IHP was foundry for EN5360



**EN5382  
800 mA**

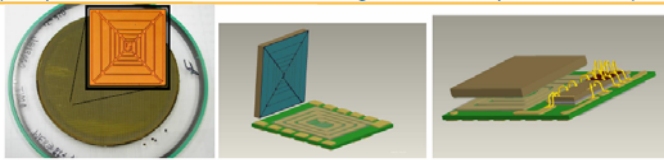


AWG30 (10 mil wire)

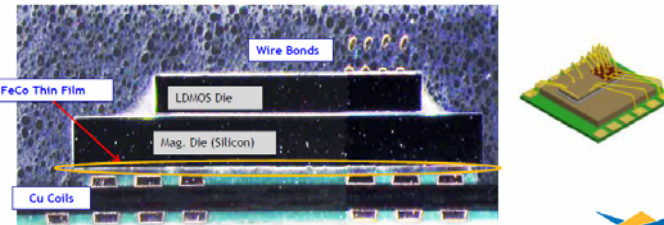
**EN5360  
6 amps**

## Introduction of Wafer Level Magnetic

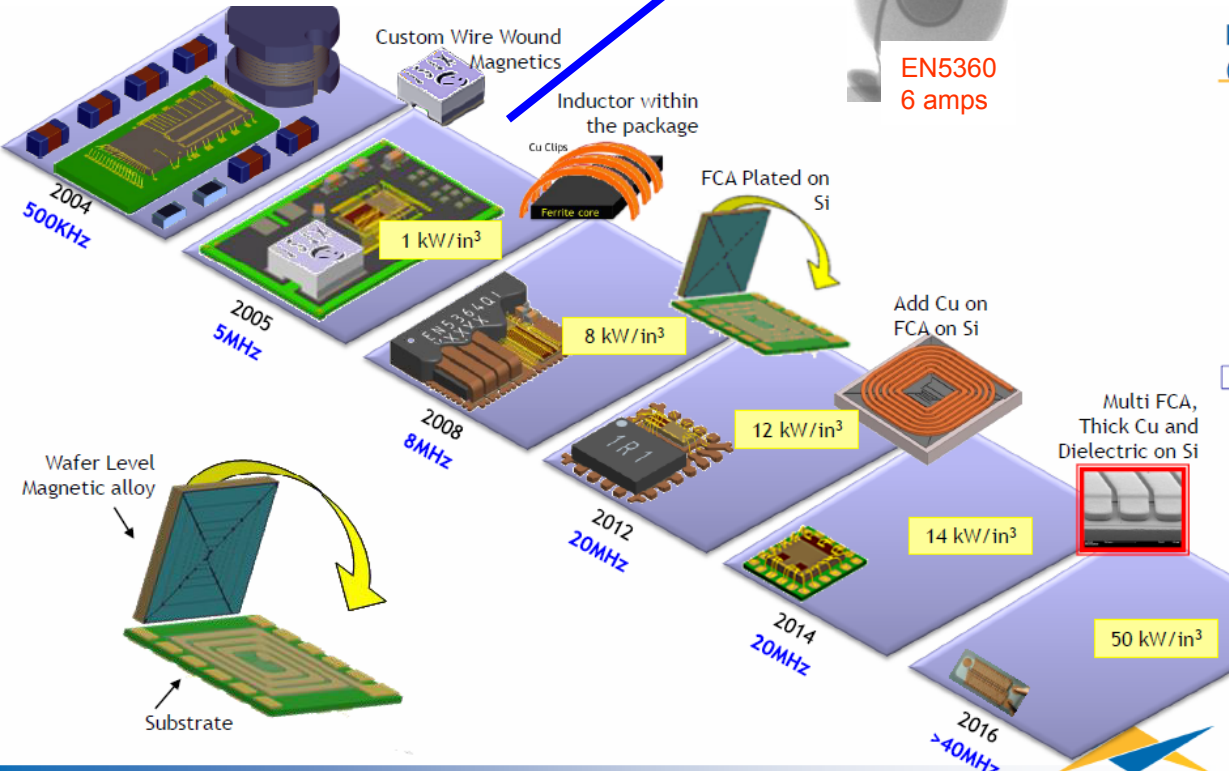
*(Simple but effective inductor design at mature process cost)*



**Step 1.** Electroplate FCA on wafer  
**Step 2.** Flip FCA over a Cu spiral coil  
**Step 3.** Package PowerSoC

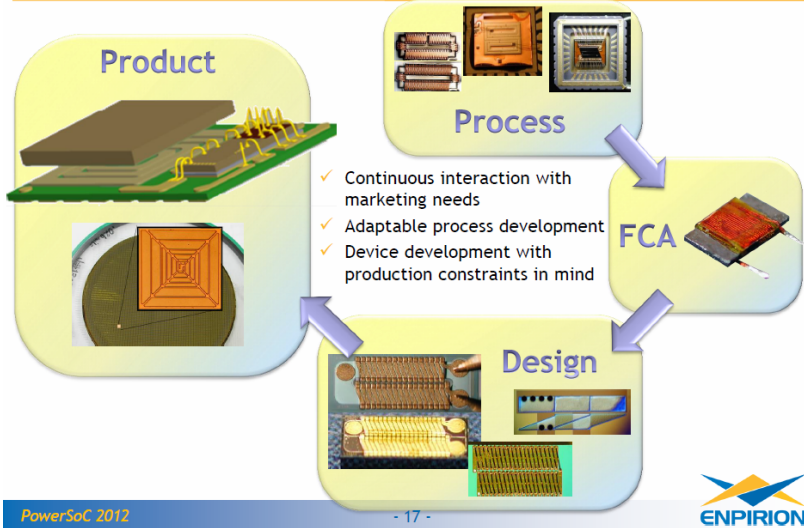


**Price ??**



# DESIGN ITERATIONS and DEVELOPMENT

(Quest For Optimum Micro-Inductor Application)

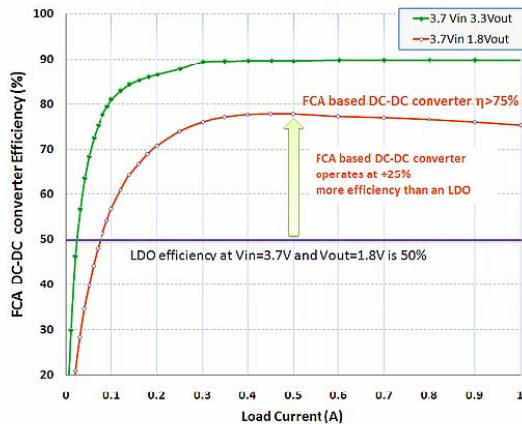


PowerSoC 2012

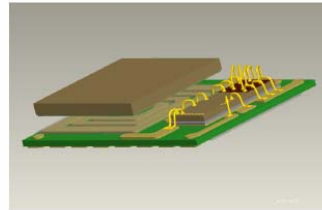
- 17 -

## FCA in Enpirion's first PwrSoC product

- ◆ Enpirion implement FCA in its first PwrSoC product
- ◆ FCA offered +25% improvement in efficiency over existing solutions



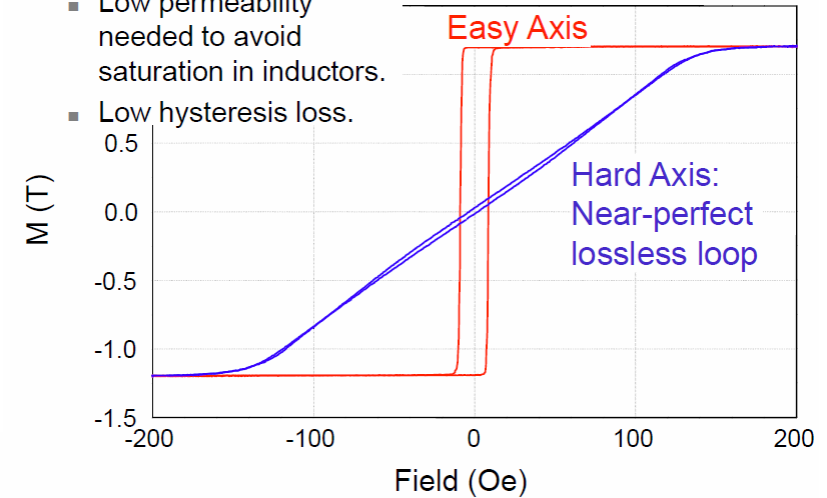
## LDO Replacement by DC-DC Buck Converter



Price 97 cents quantity 1  
Distributor Future Electronics

## Magnetic anisotropy

- Hard axis loop provides:
  - Low permeability needed to avoid saturation in inductors.
  - Low hysteresis loss.



power.thayer.dartmouth.ε

PowerSoC 2012

- 24 -



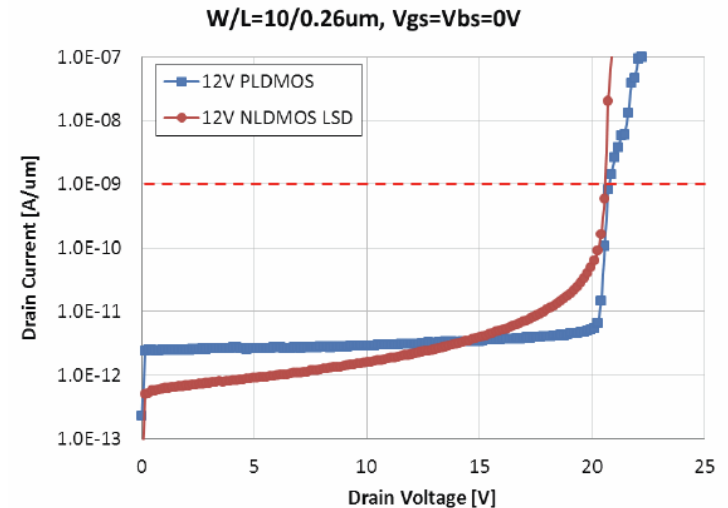
## 12 V – 1 V, 1 amp Converter @ > 25 MHz

- Over 20V off-state breakdown voltage with low leakage
- 4A, 6A, 9A, 15A in production, 20A and 40V product in develop.
- Ft and Fmax characteristics according to Vgs at Vds=6V
- Ft,max/Fmax = 37.2GHz/66.9GHz for 12V RF NLD MOS LSD
  - Ft,max/Fmax = 12.9GHz/38.4GHz for 12V RF PLD MOS

Implementation of Low Vgs (1.8V) 12V RF-LDMOS for High-Frequency DC-DC Converter Applications

**Abstract**—a 12V low Vgs (1.8V) RF-N/PLD MOS have been successfully implemented on the 0.18 μm analog CMOS process without thermal budget addition. N- and P-ch LDMOS needs additional body and drift implants, respectively. A short channel length and a small overlap of gate-to-drain were accomplished by the optimization of implant conditions for the source halo and the drift region which is followed by the gate formation with **30 Å gate oxide**. Cut-off frequency 37.2GHz and 12.9GHz each for NLD MOS and PLD MOS were achieved with breakdown voltage of 20V. The long-term wafer level HCI test result showed Idlin shift under 10% after 150Ksec stress at Vds=12V and Vgs=1.8V.

Dongbu HiTek  
 0.18 μm platform for Power Management



OFF State Breakdown Voltage

High-Frequency LDMOS in 0.18 μm BCD Technology for Power Supply-On-Chip  
 The 3rd International Workshop on Power Supply on Chip (PowerSoC2012)  
 November 16-18, 2012, San Francisco, CA, USA



# Can We Have High Radiation Tolerance & Higher Voltage Together ???

Higher radiation tolerance needs thin oxide  
while higher voltage needs thicker oxide – Contradiction ?

Mixed signal power designs from TI, TSMC, IBM etc - 0.18  $\mu\text{m}$  & 0.13  $\mu\text{m}$   
Automobile Market. Voltage ratings 10 - 80 Volts  
Deep sub-micron but thick oxide

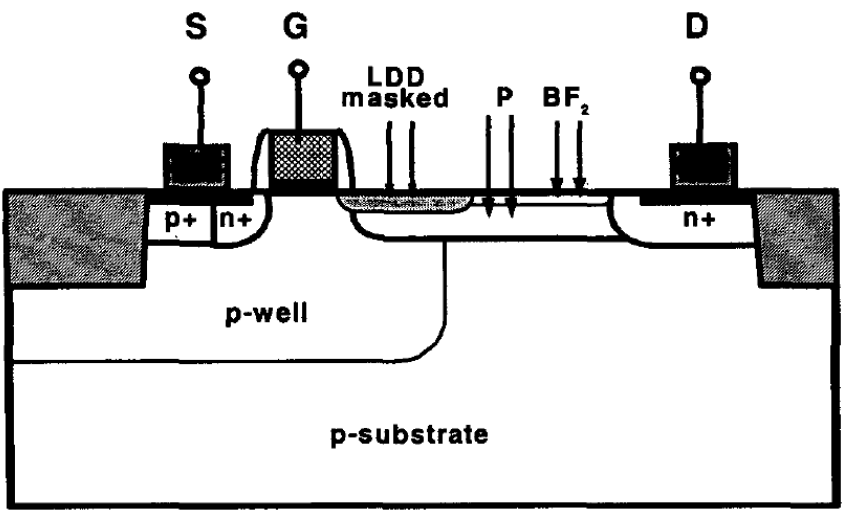
Controller : Low Voltage

High Voltage: Switches – some candidates HV & Thin oxide

RF Process LDMOS, Drain Extension, Deep Diffusion etc

>> 20 Volts HEMT GaN on Silicon, Silicon Carbide, Sapphire

**LDMOS Structure**  
Laterally Diffused  
Drain Extension



High Voltage / high Frequency  
Main market. Cellular base stations

Fig.1: Schematic cross-section of the RF-LDMOS transistor.

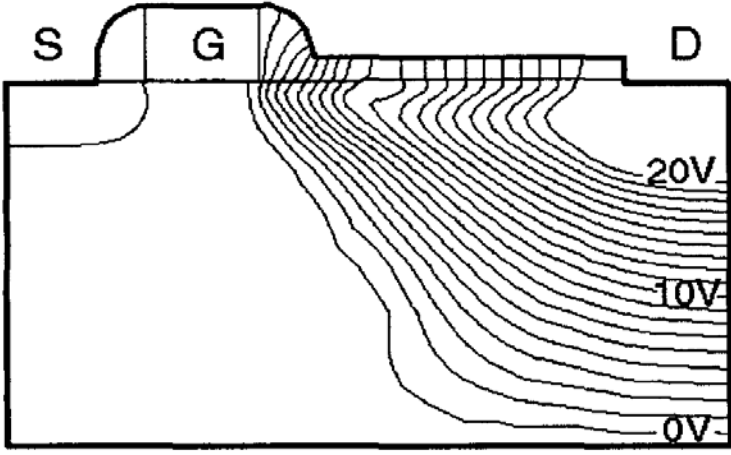


Fig.3a: Potential distribution at the highest operating voltage (20V) with  $V_G=0V$  (LDMOS 3 from Table 1).

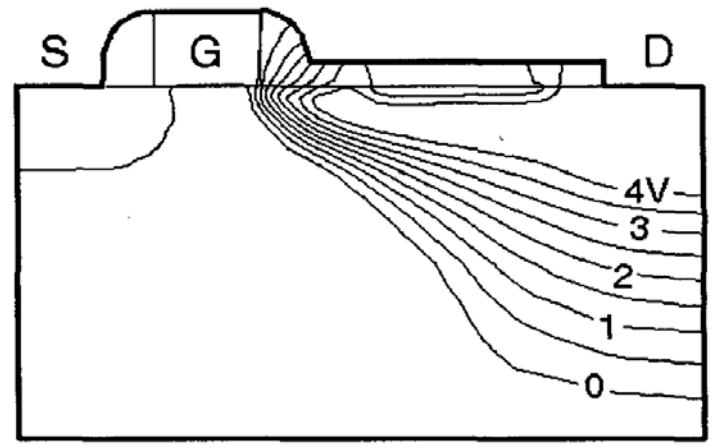


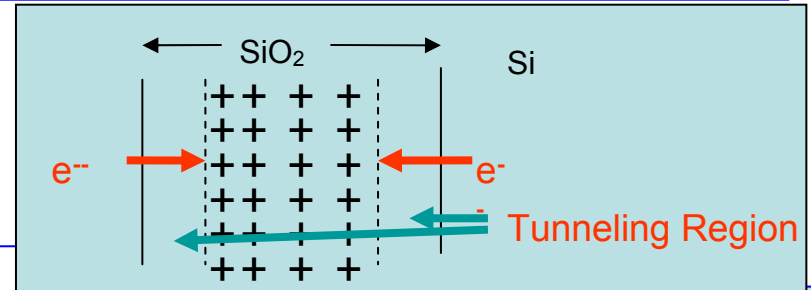
Fig.3b: Potential distribution at the lowest operating voltage (4V) with  $V_G=0V$  (LDMOS 3 from Table 1).

High performance RF LDMOS transistors with 5 nm gate oxide in a 0.25  $\mu\text{m}$  SiGe:C BiCMOS technology: IHP Microelectronics  
[Electron Devices Meeting, 2001. IEDM Technical Digest. International](#)  
 2-5 Dec. 2001 Page(s):40.4.1 - 40.4.4

# Radiation Tolerance: Thin Gate Oxide & LDMOS Structure

IBM 6SF 0.25  $\mu\text{m}$  Process. Many LHC Custom ASICs.  $T_{ox}$ = 5 nm (2.5V). 7 nm (3.3V). Radiation Hard for LHC Logic Circuits

Following are Drain extension / LDMOS Structures



Hole removal process by tunneling in thin-oxide MOS Structures  
Sachs et. al. IEEE Trans. Nuclear Science NS-31, 1249 (1984)  
Book. Timothy R Oldham  
"Ionizing Radiation Effects in MOS Oxides" 1999 World Scientific

IHP Microelectronics Fab Only – no standard products

2005 EN5360. First 5 V 5 MHz converter. 0.25  $\mu\text{m}$  5 nm Gate Oxide. 100 Mrads

2007 Increased LDMOS  $V_{in}$  operating to >12 volts

Dongbu HiTek

Lower cost version of EN5360 – **NOT Radiation Hard**

Implementation of Low  $V_{gs}$  (1.8V) 12V RF-LDMOS for High-Frequency DC-DC Converter Applications, ISPSD 2012 June 2012, Bruges, Belgium

12 > 1 V converter 25 MHz Converter

Gate Oxide = 3 nm Breakdown Voltage is 20 Volts

Texas Instruments

High Voltage (up to 20V) Devices Implementation in 0.13  $\mu\text{m}$  BiCMOS Process Technology for

**System-On-Chip (SOC) Design. ISPSD 2006, Naples, It**

20 Volt devices in 0.13  $\mu\text{m}$  BiCMOS Process

2012 80 V Power Transistors (2 amps) in 0.18  $\mu\text{m}$  Process with Gate oxide 12 nm

**LBC8** (180nm, 20-60V) and **LBC9** (130nm, 20V). 7 nm Gate Oxide for 20 volts

2009 XySemi Inc,

Founder Designed original EN5360

2 amp Power FET Transistor. 7 nm Gate Oxide. Process HV MOS20080720. Radiation Tested to 52 Mrads

2010 National Semiconductor LM2864 20V/4 amps Process PVIP25 11.8 nm 1 Mrads

## Electrical Properties of Wide Bandgap Semiconductors Compared With Si and GaAs

<b>Material</b>	$E_g$ (eV)	$\epsilon_s$	$\mu_n$ (cm <sup>2</sup> /Vs)	$E_c$ (MV/cm)	$v_{sat}$ (10 <sup>7</sup> cm/s)	$n_i$ (cm <sup>-3</sup> )	<b>BFOM*</b>
Si	1.12	11.8	1350	0.3	1.0	1.5x10 <sup>10</sup>	1
GaAs	1.42	13.1	8500	0.4	2.0	1.8x10 <sup>6</sup>	17
4H-SiC	3.26	10	720	2.0	2.0	8.2x10 <sup>-9</sup>	134
6H-SiC	2.86	9.7	370	2.4	2.0	2.4x10 <sup>-5</sup>	115
2H-GaN	3.44	9.5	900	3.0	2.5	1.0x10 <sup>-10</sup>	537

$E_g$ , bandgap;  $\epsilon_s$ , dielectric constant;  $\mu_n$ , electron mobility;  $E_c$ , critical electric field;  $v_{sat}$ , saturation velocity;  $n_i$ , intrinsic carrier density.

\*BM= $\epsilon\mu E_c^3$ , BFOM was normalized by the BM of Si.

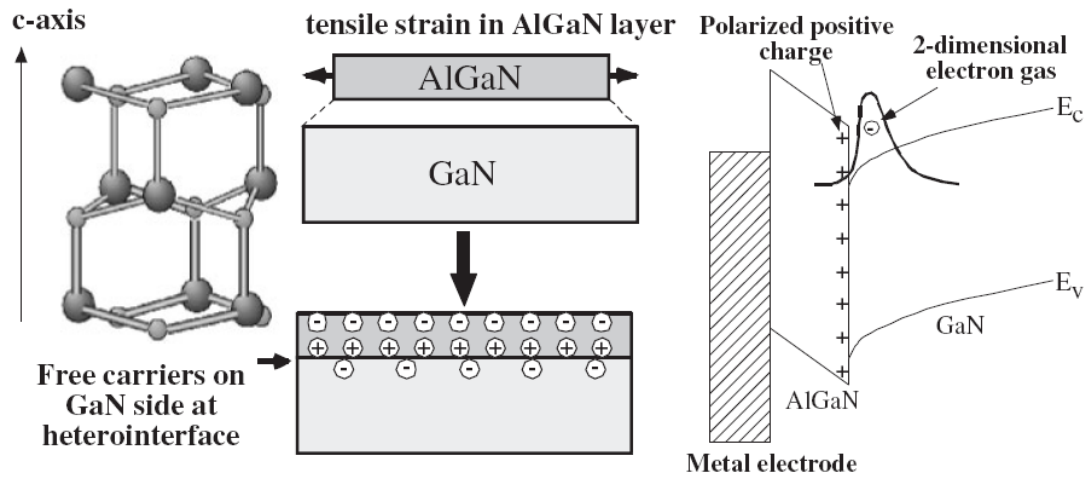


Fig. 6. AlGaIn/GaN heterostructure and its band diagram. When the AlGaIn layer is under tensile strain, free carriers are accumulated at the heterointerface owing to the piezoelectric effect caused by the strain, and a spontaneous polarization effect.

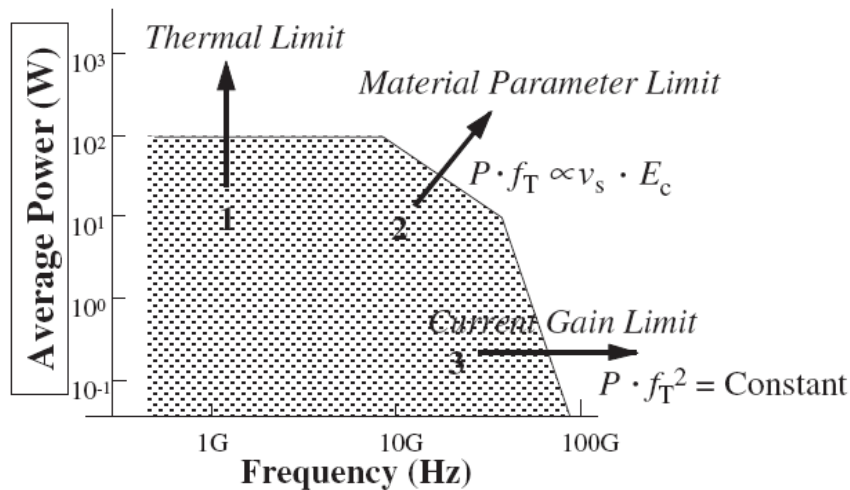


Fig. 7. Restrictions of HF devices in terms of output power and frequency. The limiting factors for HF device operation are thermal restriction, material property restriction and current gain restriction, for the respective regions shown in the figure.

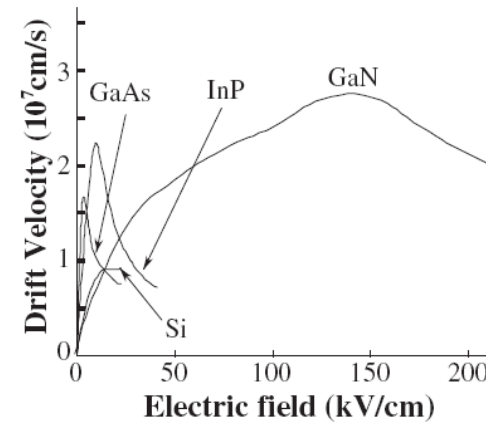


Fig. 8. Dependence of drift velocity of semiconductors on electric field. GaAs and InP have high mobilities (slope of drift velocity–electric field relation in the low-electric-field region); however, their drift velocities decrease in the high-electric-field region. On the other hand, GaN shows high drift velocity in the high-electric-field region.

# Gallium Nitride Devices Tests 2009

## RF GaN 20 Volts & 0.1 amp

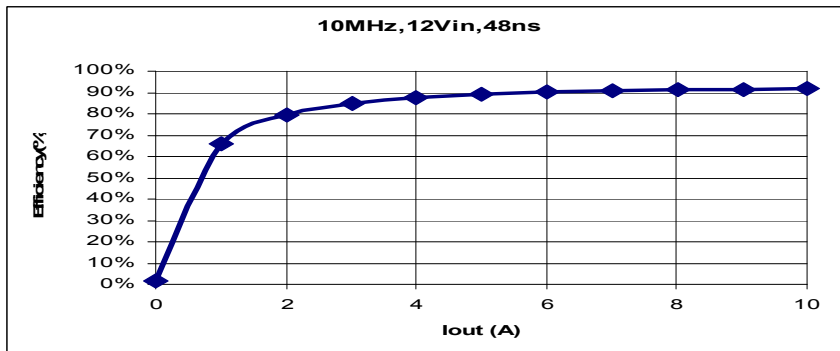
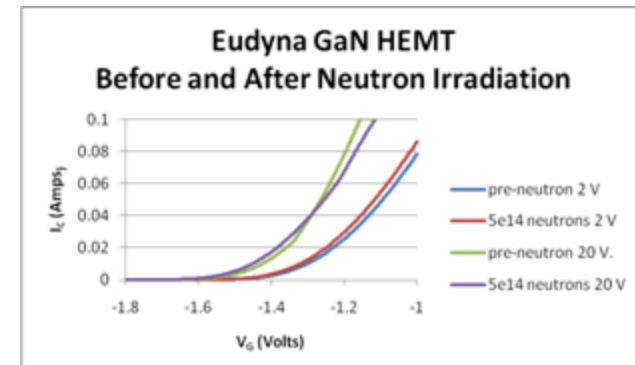
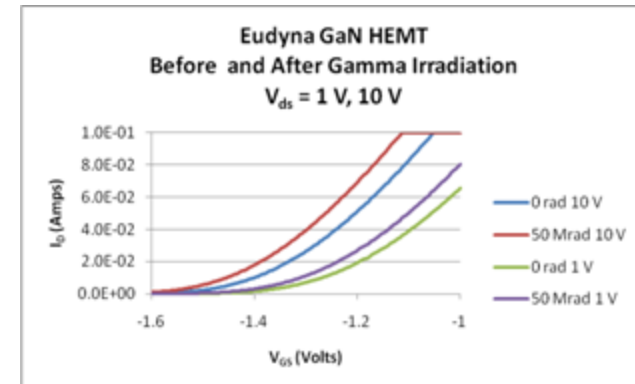
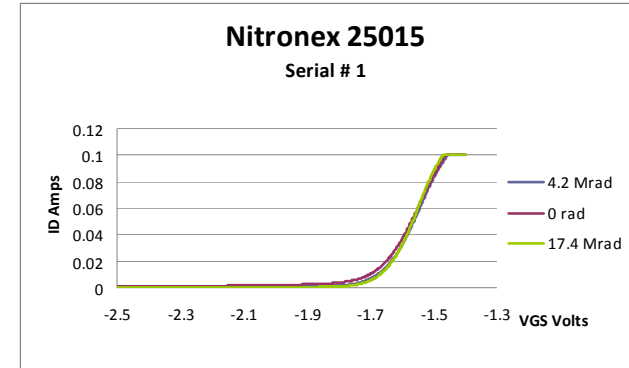
- ❖ 8 pieces: Nitronex NPT 25015: GaN on Silicon
- ✓ Done Gamma, Proton & Neutrons
- ✓ 65 volts Oct 2009 **48V Converter?**

- ❖ 2 pieces: CREE CGH40010F: GaN on siC

- ❖ 6 pieces: Eudyna EGNB010MK: GaN on siC
- ✓ Done Neutrons

## Switch GaN

- ❖ International Rectifier GaN on Silicon
- Good efficiency to >12 MHz Driver limited



Gamma: @ BNL  
Protons: @ Lansce  
Neutrons: @ U of Mass Lowell

Oscillations in SPA @ >>1 GHz

# Design Guide for Enhancement Mode (Normally Off) FETs

Includes radiation testing by Yale and others

This shows reducing waste heat (improved Efficiency)  
Can get more output current for the same cooling capacity

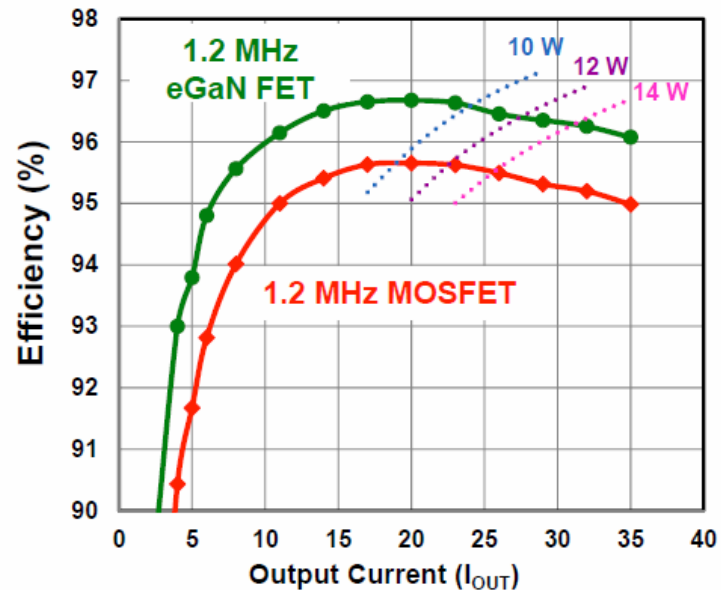
## GaN Transistors for Efficient Power Conversion

The eGaN® FET Journey Continues

Alex Lidow • Johan Strydom • Michael de Rooij • Yanping Ma  
With a Forward by Sam Davis, Senior Editor – Power Electronics Technology Magazine

FIRST EDITION

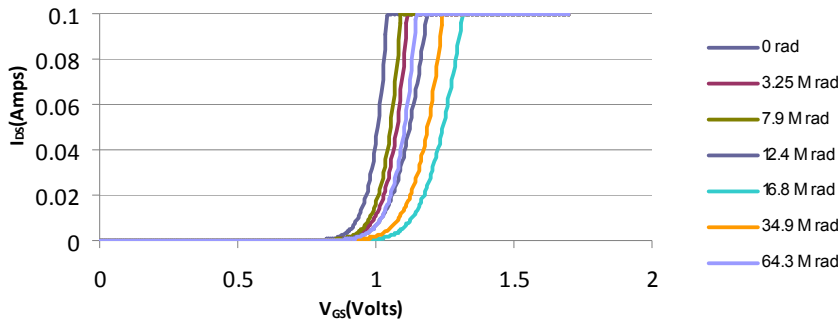
## Efficiency Comparison



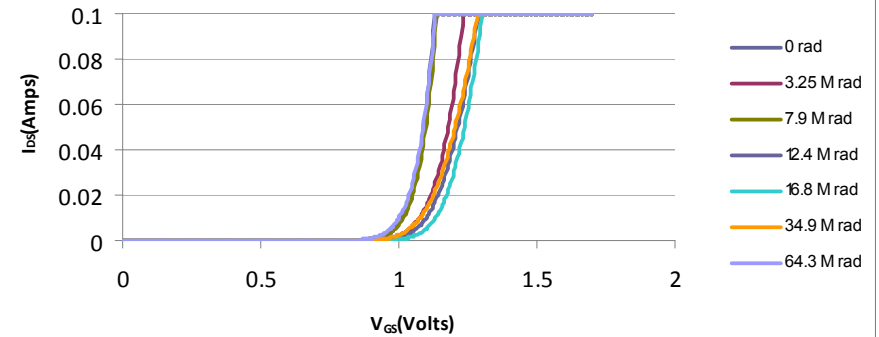
$$F_S = 1.2 \text{ MHz}, V_{IN} = 48 \text{ V}, \text{ and } V_{OUT} = 12 \text{ V}$$



### EPC 1014 DC BIAS Gamma Irradiation



### EPC 1014 CLOKED Gamma Irradiation

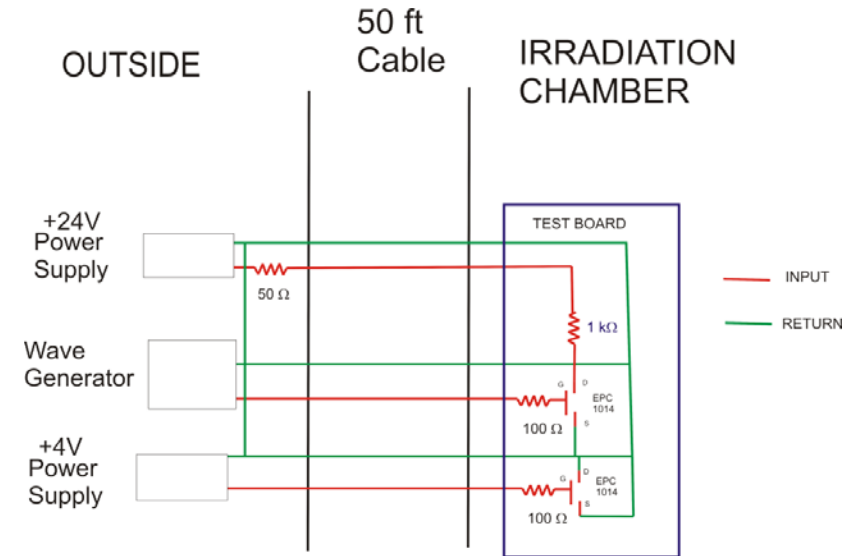


During Gamma Irradiation DC BIAS 4 VOLTS, VDS = 0  
Fluence rate= 5 mega M rad/day

## Enhancement Mode GaN FETs

### Proton Irradiation

The run went well, we left your board in the beam until it reached approximately  $1 \times 10^{15}$  p/cm<sup>2</sup> (800 MeVp). The initial measurement of voltage across the 50 ohm resistor was 0.645V, and the final measurement was 0.643V. Readings were taken after every entry to remove samples from the blue room (7 times) and they were always between 0.643V - 0.645V. I'm sure Leo Bitteker has your shipping information but you may want to send him a reminder in a couple of weeks.



Gamma Irradiation done @ BNL Gamma Facility *James Kierstead July 2010*  
Proton Irradiation @ LANSCE, Los Alamos National Lab. *August 2010*



## Converter Notes

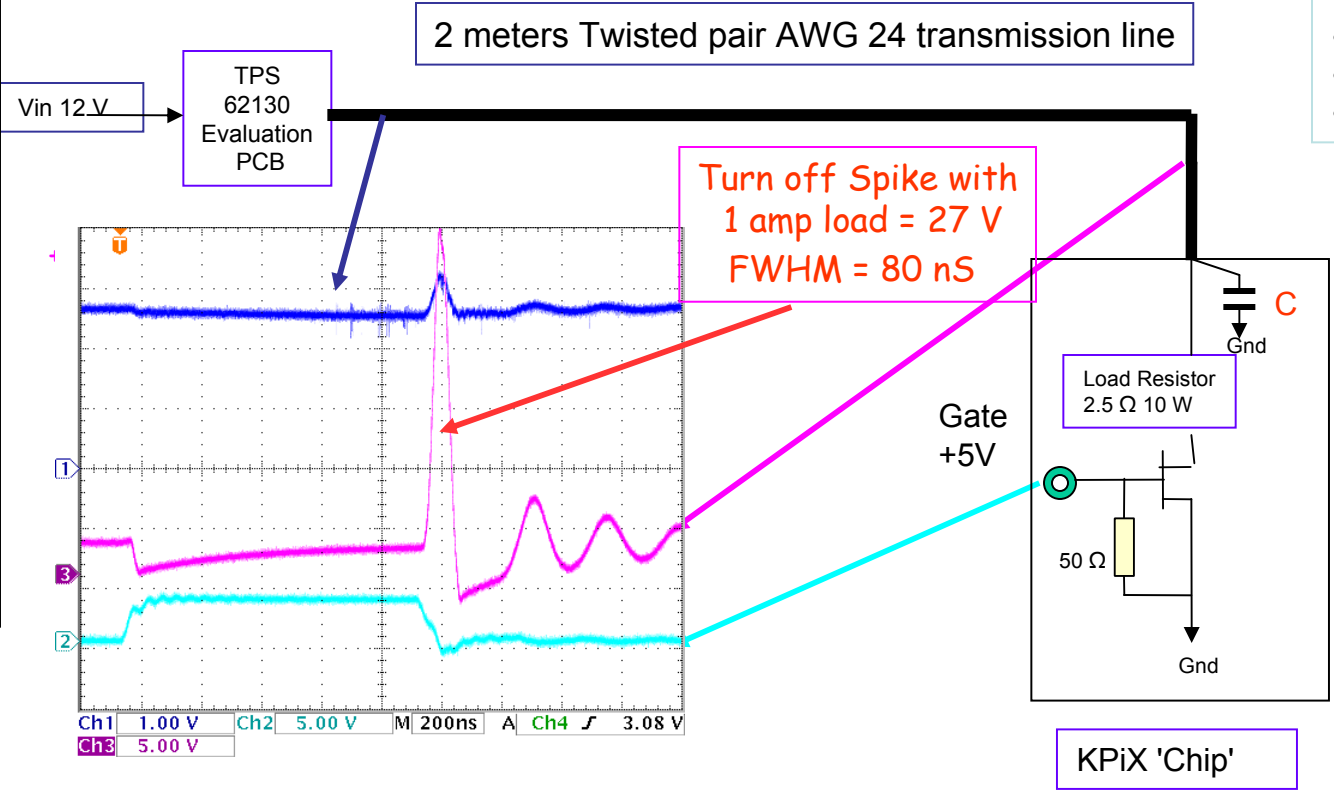
- ❖ Learned from commercial Devices, Companies & Power conferences
- ❖ Can get high Radiation Tolerance & Higher Voltage
- ❖ High Frequency > Smaller Air coil > Less Material
- ❖ Goal: ~20 MHz Buck, 1 amp *size 9 mm x 9mm*
- ❖ Power SOC: MEMs Air Core Inductor on Chip
- ❖ Study Feasibility 48 / 300V Converters
- ❖ Irradiation: Run @ Max operating V & I.
  - ❖ Limit Power Dissipation by Switching duty cycle
  - ❖ ~ 20 device – almost all failed
- ❖ Online Monitoring during irradiation for faster results

**Power Transmission Issues for SiD:**

- Want large conversion ratio to reduce Cu and thermal losses.
- Need to operate in high magnetic field: air core inductors
- Need to control  $V=Ldi/dt$  resulting from power modulation
- Must not bother sub-fC signals to KPiX!

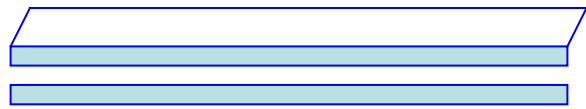
**Turn Off Spike**

- Damage IC if >20% of VCC
- Decreased with Lower Cable Z
- Engineer KpiX current turnoff

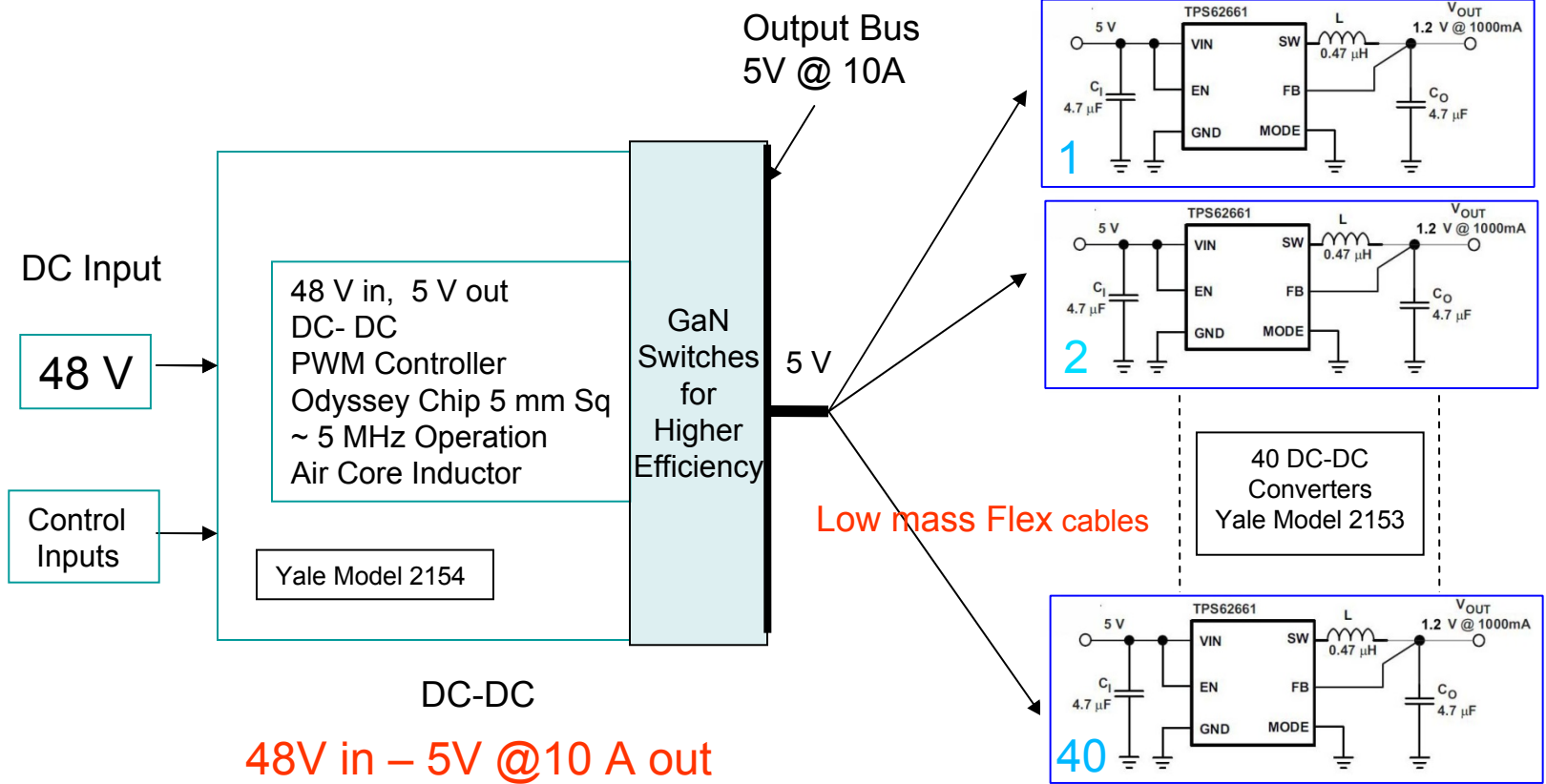


Waveforms when 1 amp flowing thru 130 Ohms twisted pair is interrupted /switched off. 27 Volt spike appears across KPiX chip. Not yet tested with real KPiX.

Cu Microstrip Line  
 $t = 9$ ,  $w = 90$  mils  
 Enamel insulation ~ 0.2 mils



# Two Stage DC-DC Power Conversion & Distribution



48V in – 5V @10 A out

Fewer of these modules further from the detector/sensors

### Status

Model 2153: Prototype for coil configurations under Test  
Model 2153: Odyssey Chip Eval Board under NDA

5V in – 1.2V @1 A out

Many of these modules close to the detector/sensors  
Low mass chip scale package  
small Air Core Inductor.  
Test 6, 9 and 20 MHz Converters

# Proposed Power Switching Tests in 7T Magnet at Yale University for SiD

- KPiX chip with & without Pulse power. Needs DAQ & Software experts to run it.
- Current leads tests – vibration, movement, tilting.



7T Magnets	Warm Bore cms	Length cms	Orientation	Access
# 1	8.9	150 ??	Vertical	Top
# 2	16	105	Horizontal	One end
# 3	16	105	Horizontal	One end



Test set up in 7 Tesla Magnet

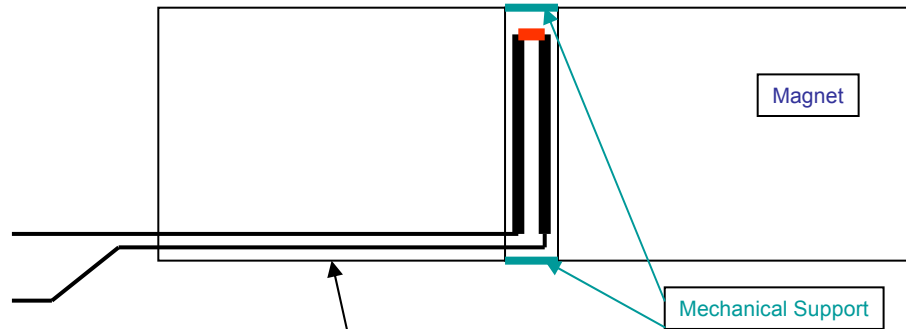
Bruker 7T, 20 cm bore

Conductors under Test  
Thin material: Kapton, Cu  
Rotate orientation

- Measurement Instruments
- Laser Interferometer
  - Capacitor Transducers
  - Capacitec Inc.
  - MEMS
  - More ....

Pulsed Current 0.1 – 5 amps

Pulser  
5 Hz

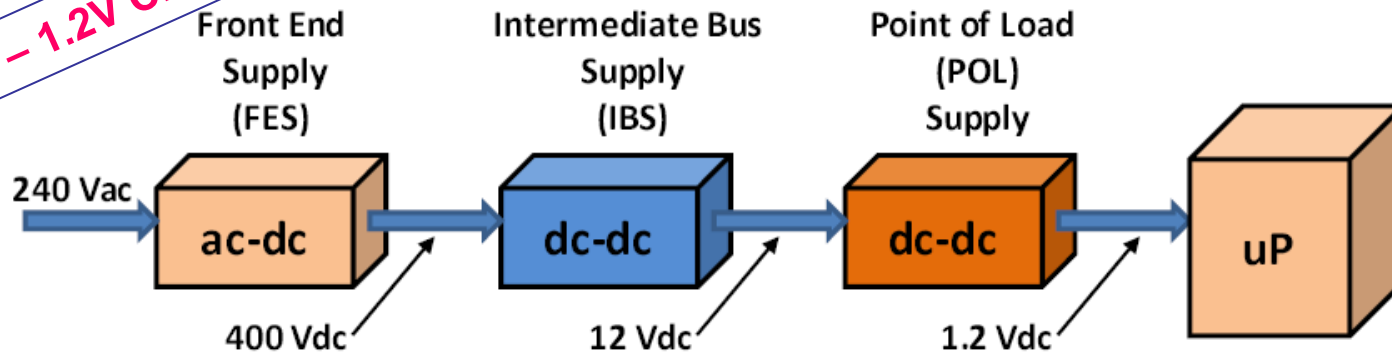


Twisted pair- round or twisted Stripline

# GaN High Efficiency Power Switching Applications

- ❖ Data Center: Efficiency sensitive / More CPU power in same vault  
400 V DC (+/-200 V) Power distribution: 12 V – 1 V converters.  
- IEC SMB SG4, IEC TC64, ETSI EE, The Green Grid -Power sub working group
- ❖ AC Line > DC power converters 600V 5 - 20 amps. Low vampire power
- ❖ Electric Vehicles 600 /900 V 100 kwatts
- ❖ Railways 8 KV SiC FETs, SiC diodes

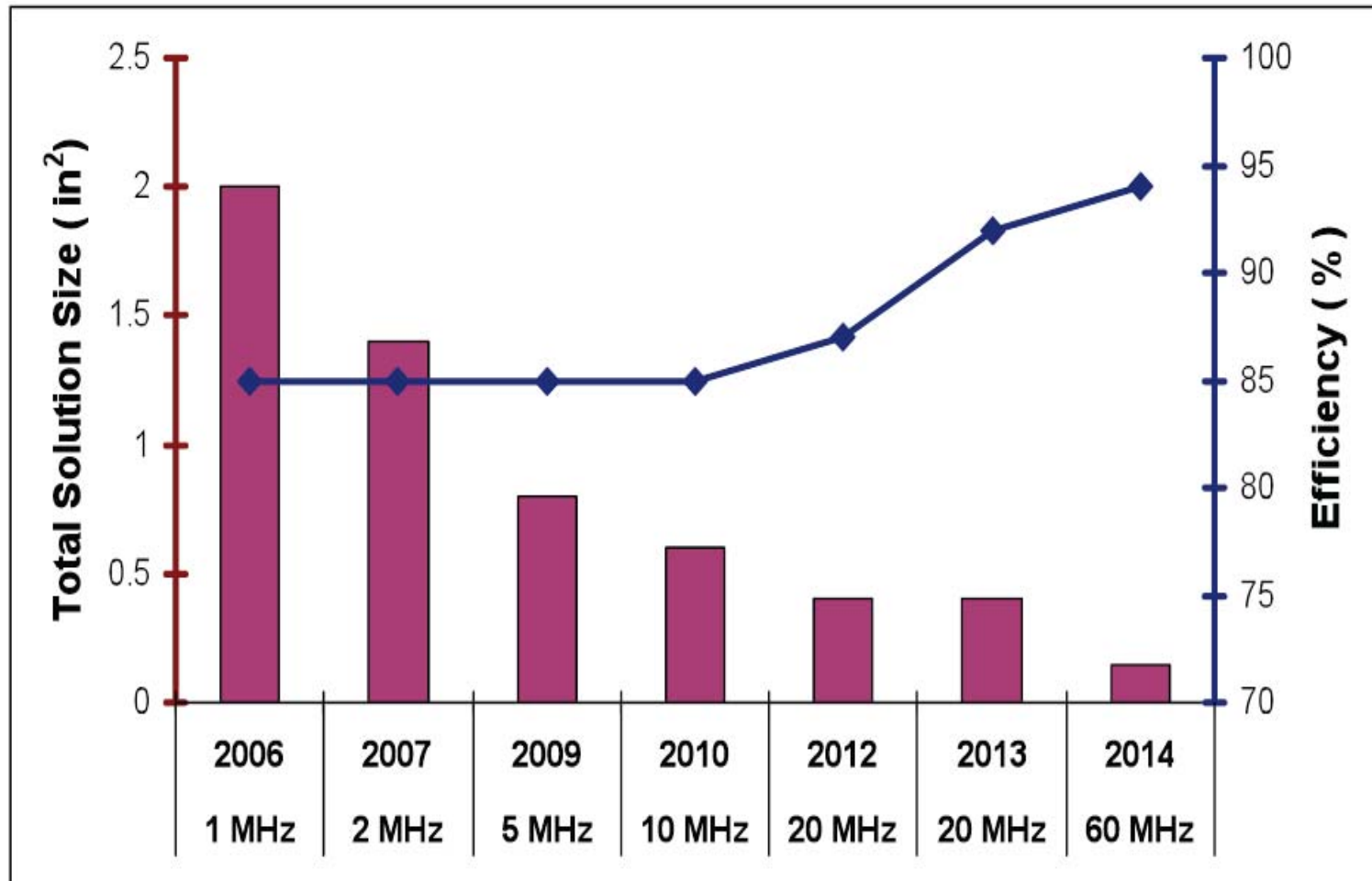
400 V – 1.2V Chain



	FES	IBS	POL	Plug-to-Processor
Recent	93%	95%	88%	78%
Best Immediate	95%	98%	90%	84%
	IBM Challenge			<b>90%</b>
Needed	98%	98%	94%	<b>90%</b>

# Potential LV DC-DC Power Stage Roadmap

Optimized Performance – Without tradeoff



12Vin, 1.2Vout, 100A      Based on Circuit Simulation

For high frequency Integrate a GaN Driver into Power Stage !

# High Voltage Distribution Bus- IBM

## EPA 80 PLUS Energy Star Rating

		% Load				
		10	20	50	100	
<i>Rating</i>	<b>Bronze</b>		81	85	81	
	<b>Silver</b>		85	89	85	
	<b>Gold</b>		88	92	88	
	<b>Platinum</b>		90	94	91	
	<b>Titanium</b>		90	94	96	91

New Standard under Consideration for Power Products

# Panasonic Integrated GaN Inverter for small Motors, Air Conditioners, Refrigerators

## GaN Power Switching Devices

Masahiro Ishida\*, Yasuhiro Uemoto\*\*, Tetsuzo Ueda\*, Tsuyoshi Tanaka\*, and Daisuke Ueda\*\*\*

\*Semiconductor Device Research Center, Semiconductor Company, Panasonic Corporation,  
1 Kotari-yakemachi, Nagaokakyo-shi, Kyoto 617-8520, Japan

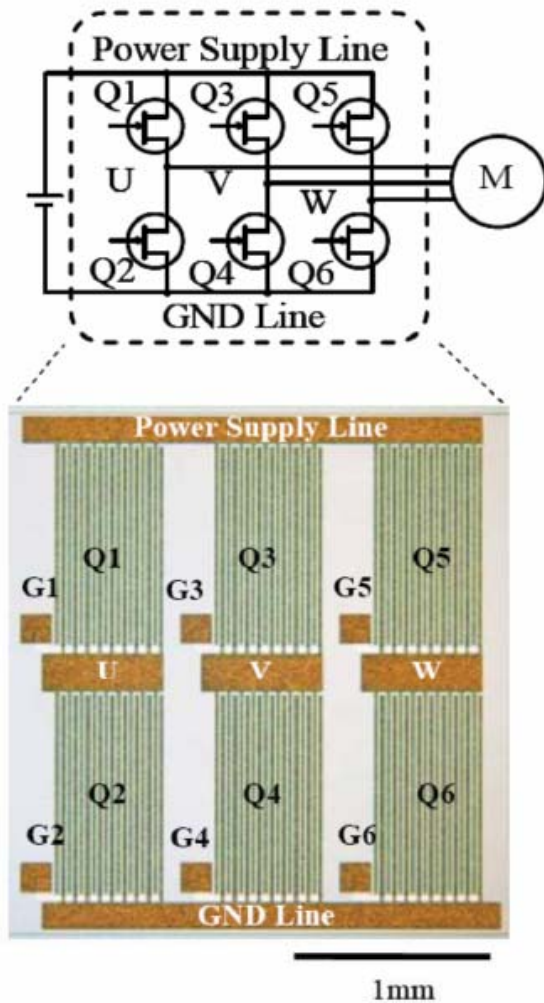


Fig.8 Circuit diagram and chip photograph of fabricated GaN monolithic inverter IC using GITs on Si.

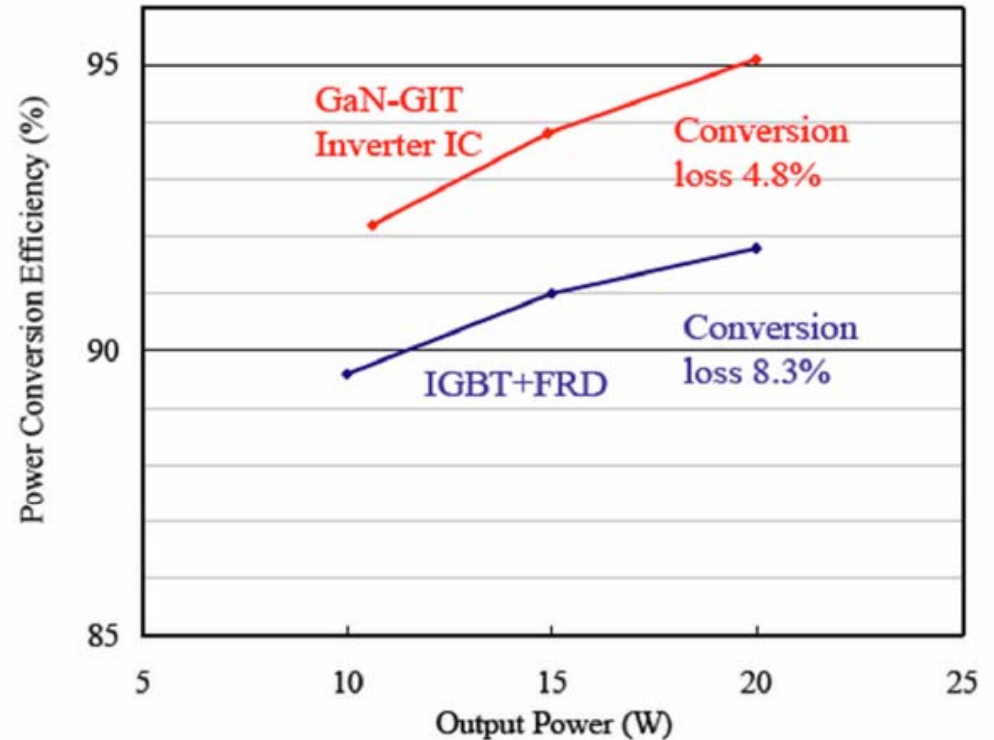
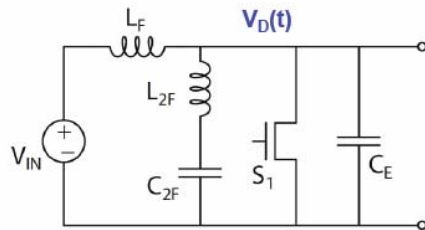
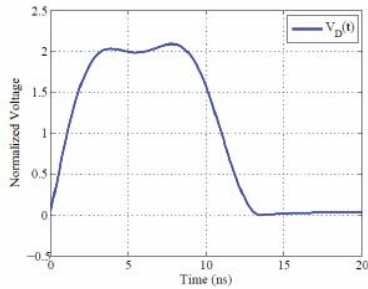


Fig.10 Power conversion efficiency of GaN monolithic inverter and that by conventional Si-IGBTs with FRDs at various output power of the motor.

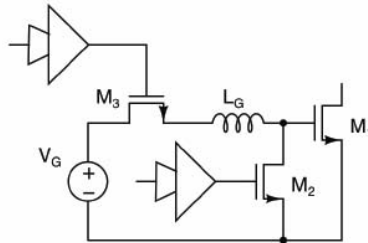
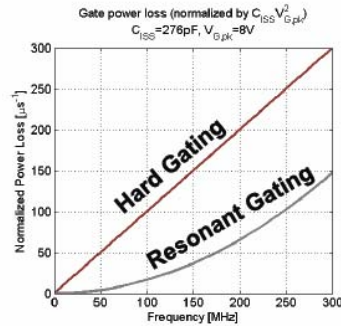


- Minimize frequency dependent device loss, switch fast enough to change or eliminate magnetic materials

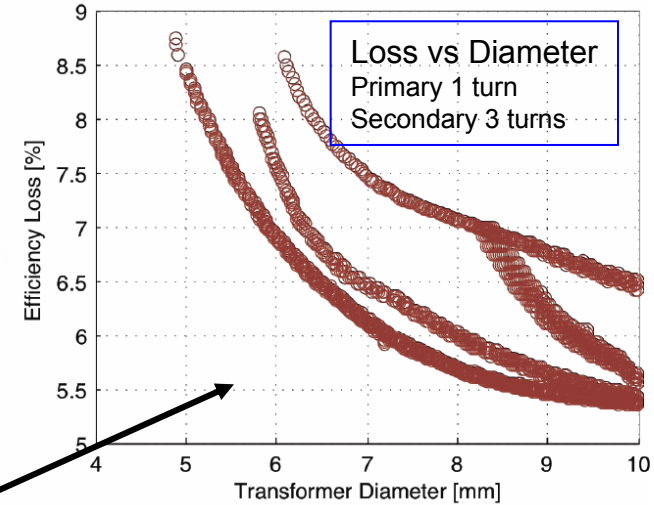
## ZVS Soft switching



## Resonant gating



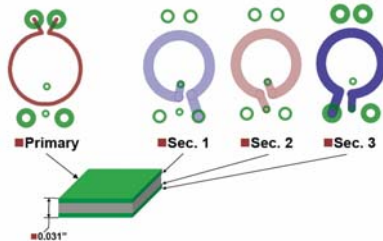
## Coreless magnetics in package or substrate



## Coreless Planar PCB Transformer



- Design transformer as a planar structure in a printed circuit board
- 4-layer PCB, 0.031" thickness for initial prototypes



Higher frequency into the VHF range offers minaturization, integration, bandwidth

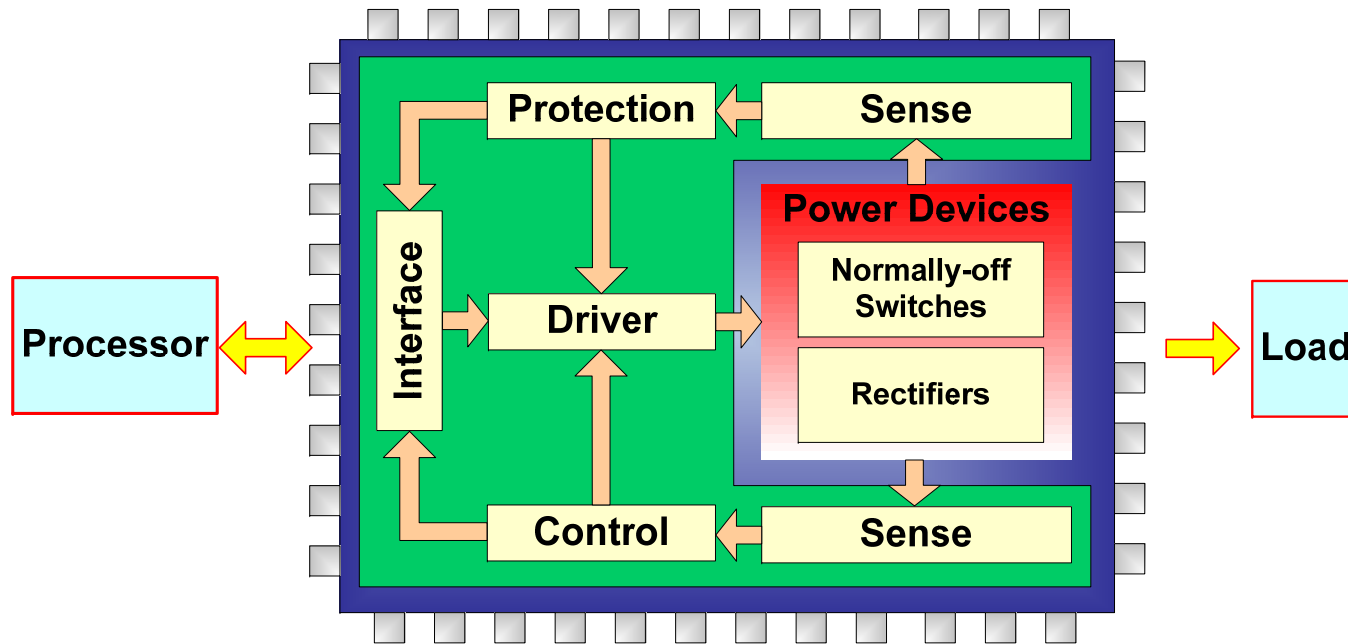
- Must overcome switching, gating and magnetics losses
- Must *manage and apply* parasitics

- Converter examples at 10's of Volts and Watts

12.1 A Method to Optimize Integrated LDMOS Transistors for Use in Very-High-Frequency (30-300MHz) DC-DC Converters

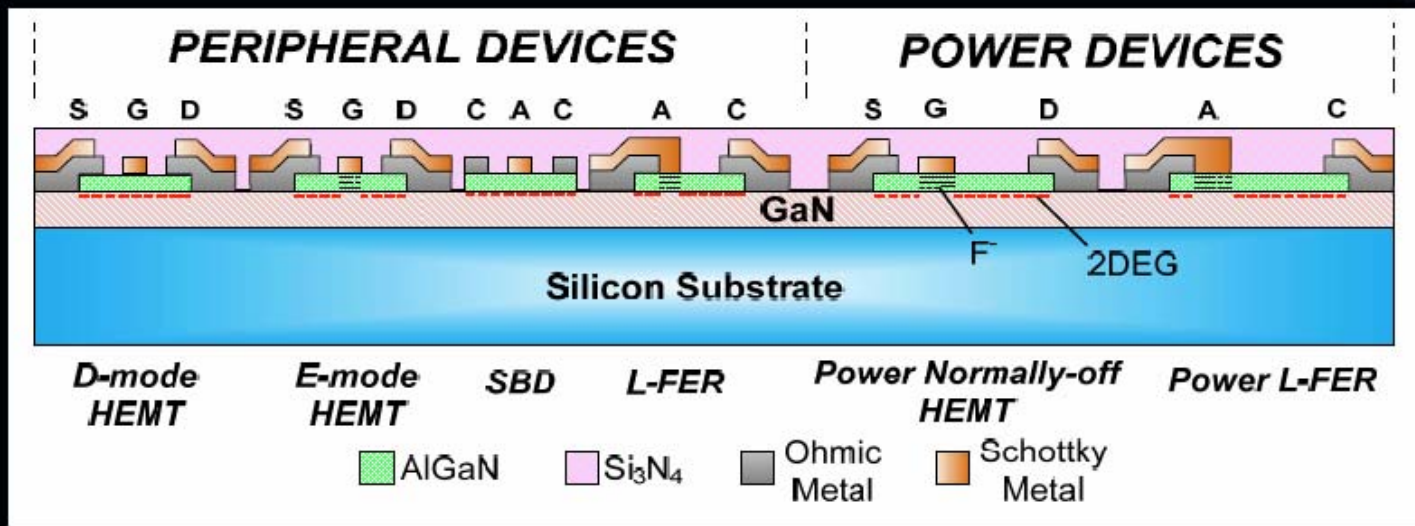
Anthony Sagneri  
OnChip Power

# Implementation of GaN power modules



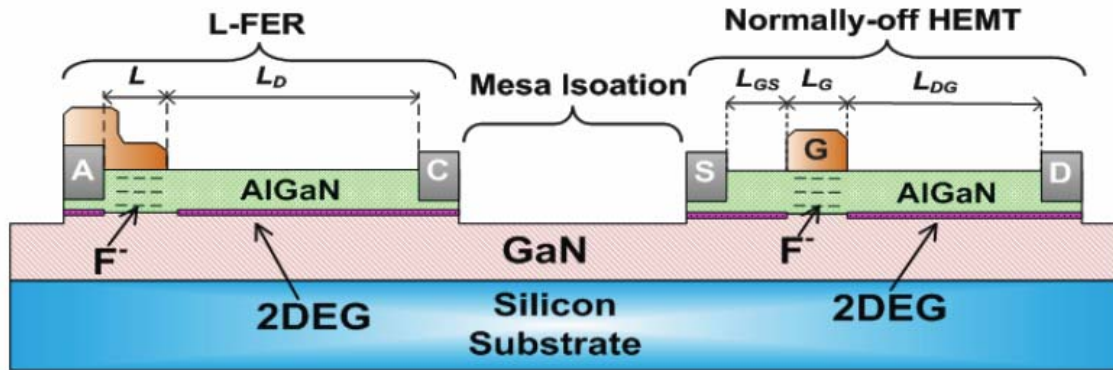
- **Multi-chip modules:** GaN(power)+Si CMOS (peripheral circuits)
  - quick design turn-around, development is underway
  - *operating temperature limit set by Si*
- **All-GaN single-chip solution:** long development time for GaN digital/analog ICs, wide temperature range

# GaN Smart Power Technology Platform

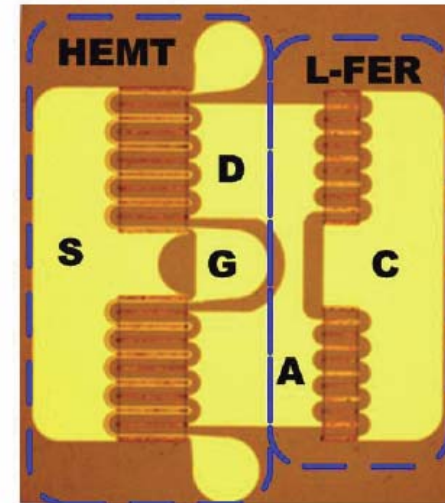
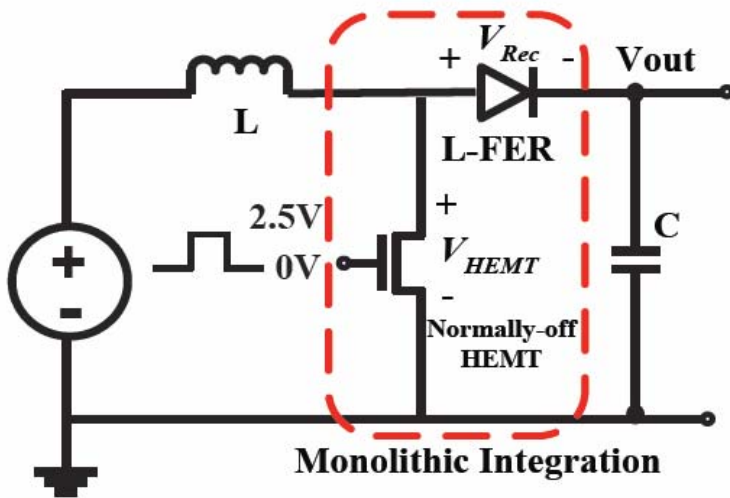


Power Devices	Smart Part	
❖ Normally-off HEMT	<b>Digital:</b>	<b>Analog:</b>
❖ Lateral Field-Effect Rectifier (L-FER)	Direct-coupled FET logic (DCFL)	Sensing & Protection

# Monolithic integration of HEMT and L-FER

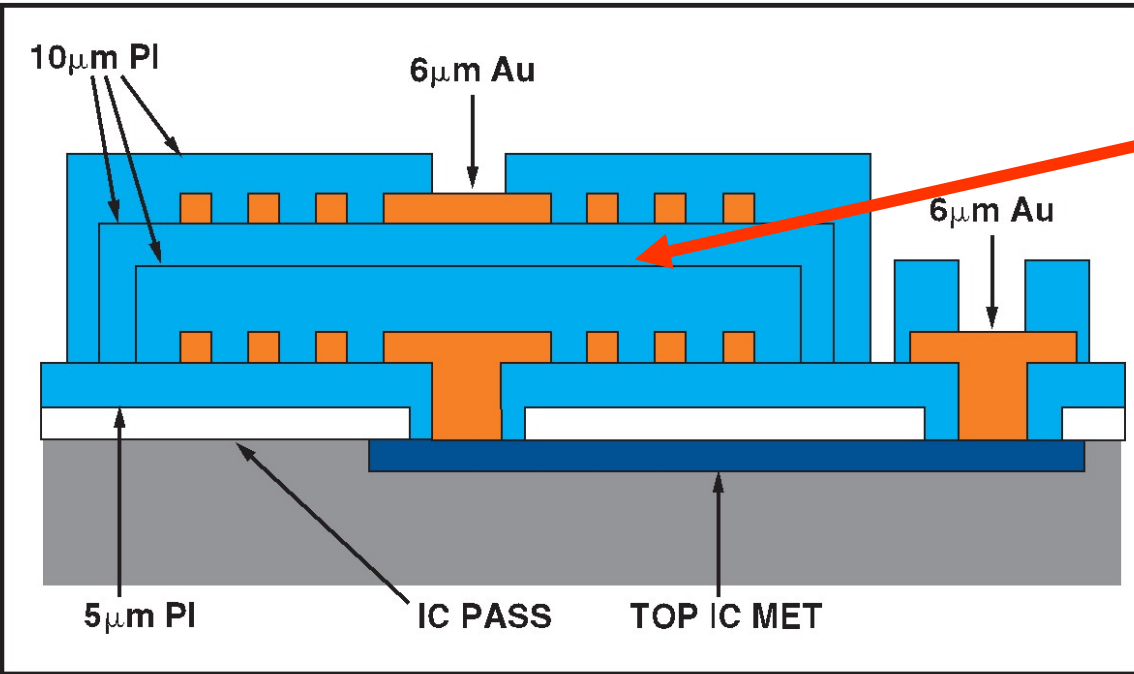


W. Chen, et al., *APL*, 2008,  
*IEEE EDL* 2009  
 W. Chen, et al., *IEDM*  
 2008.



L-FER: Lateral Field Effect Rectifier





Intra coil Insulation  
Polyimide (Kapton)

Q @300 MHz  
Top Coil = 20  
Bottom Coil = 15

Technology CMOS  
0.35 µm & 0.6 µm

Figure 2. Cross section of iCoupler transformer coil.

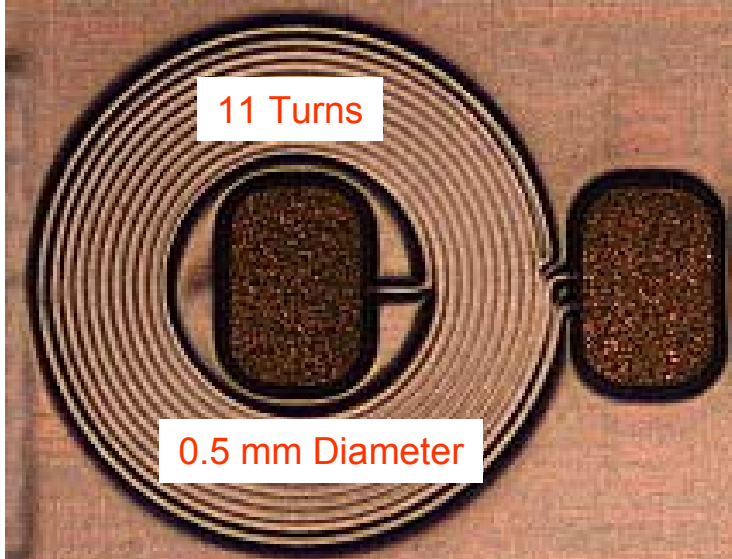
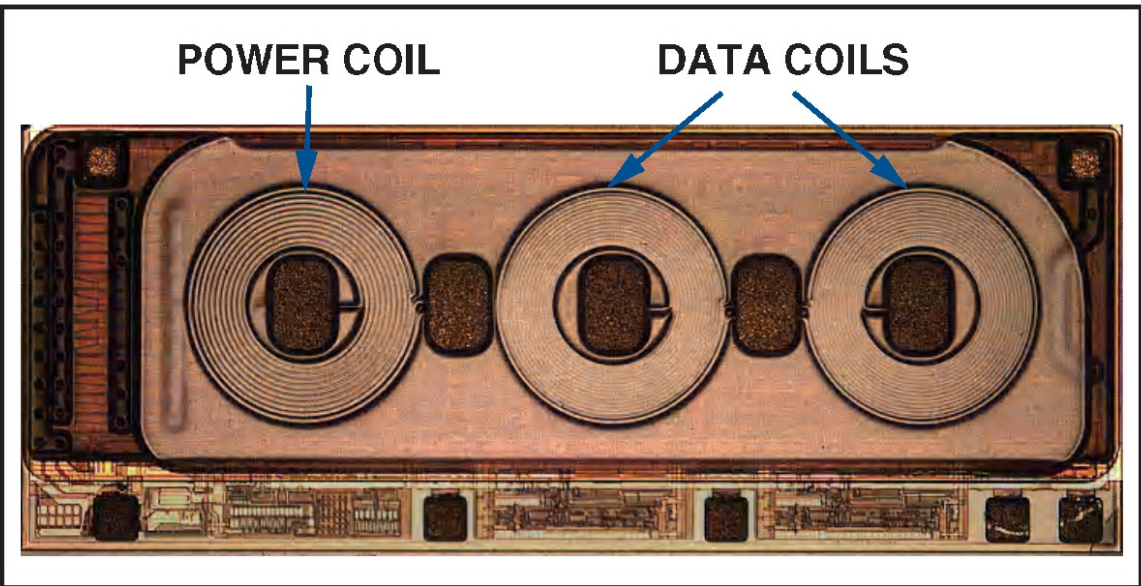


Figure 3. Photograph of transformer die showing the power transformer coil and the two data transformer coils.

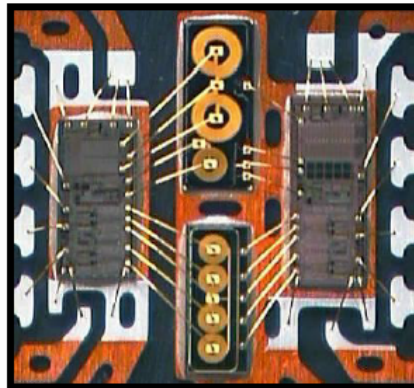
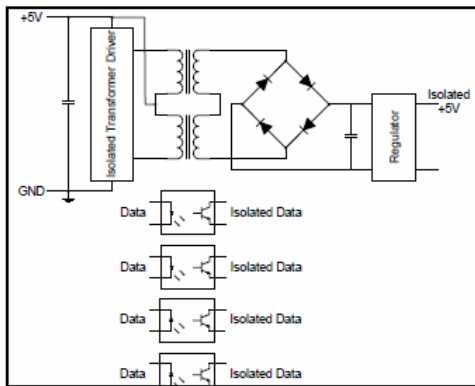
# Developing the Next Generation of *isoPower*

## Magnetic Core *iCoupler*® Transformers

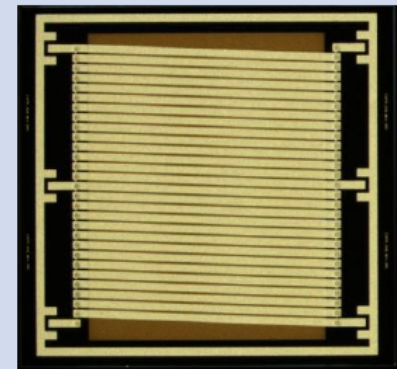
Discrete solutions with optocouplers and external transformers are Large, Custom designs with Poor Reliability.



Proprietary *isoPower* integrates data & power in one package.



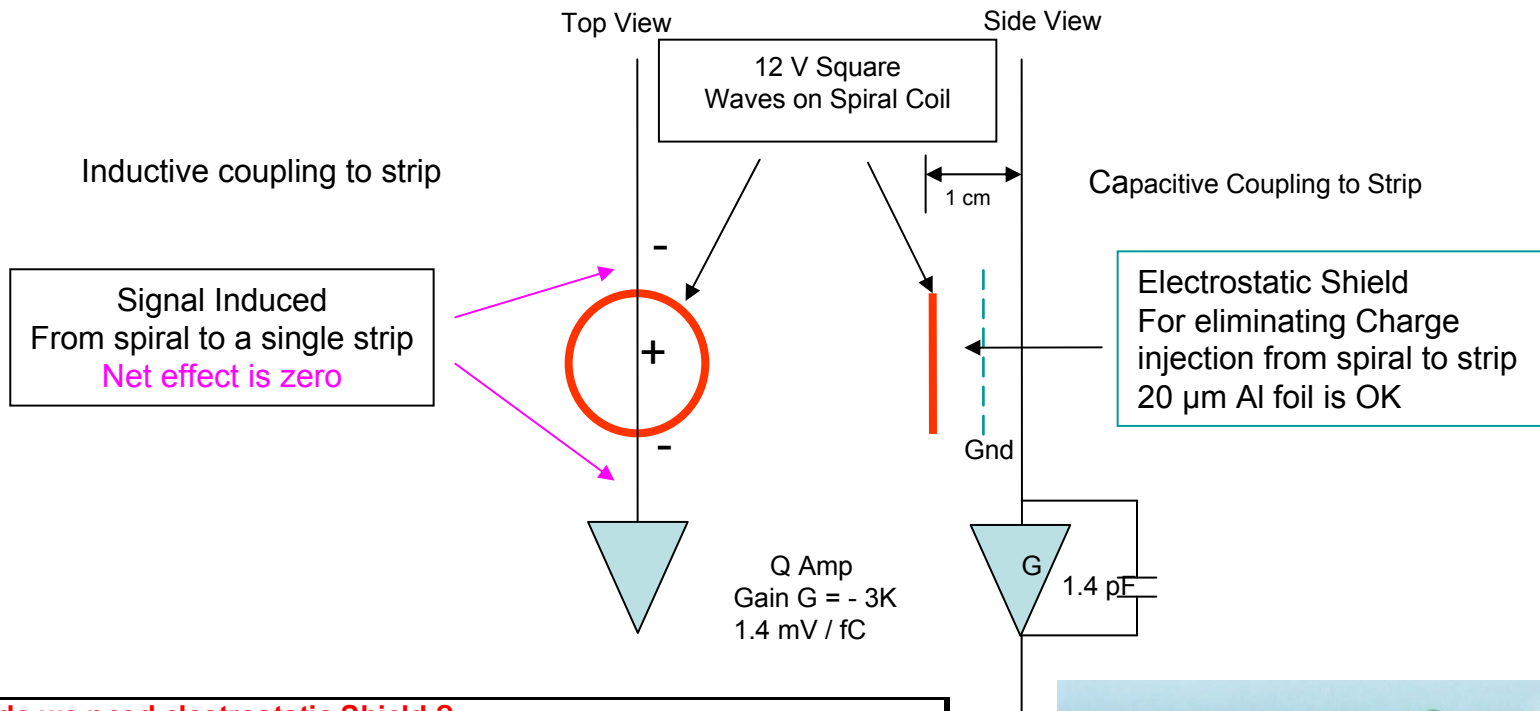
Today's air core transformers will be replaced with magnetic core transformers.



**Magnetic Core *isoPower***

- Better Efficiency & Power
- Low Noise Emissions (EMI)

# Why an Electrostatic Shield ?



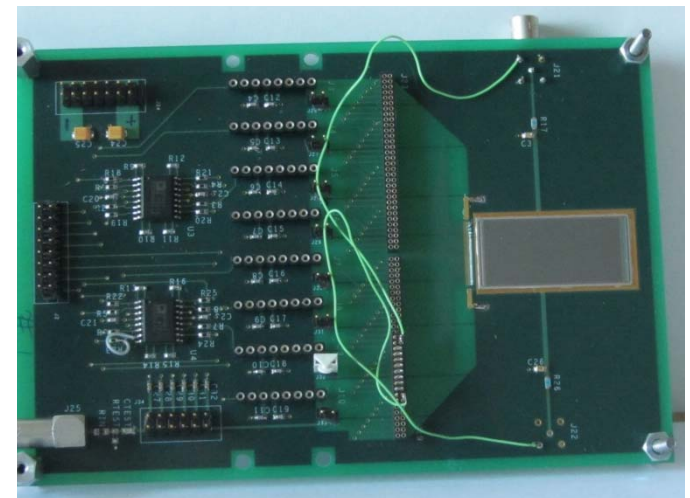
## Why do we need electrostatic Shield ?

Parallel Plate Capacitance in pF =  $0.225 \times A \times K / \text{Distance}$

	Inches	C in femto farads
Area =	1	
Distance =	0.4	500
GLAST = .5 x 1.3	0.6	
per strip= 0.6 /48	0.0125	6.25

1 volt swing on spiral coil will inject Q= 6 femto Coulombs

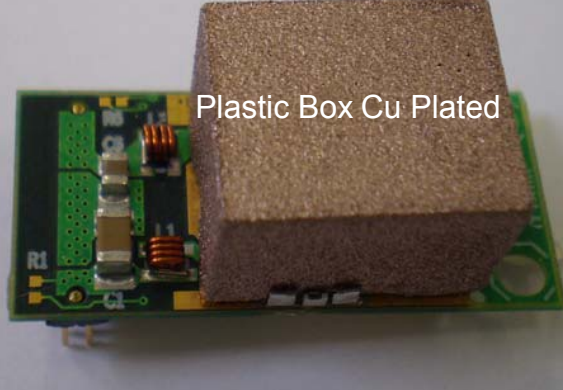
Charge from one minimum ionizing particle (1 mip) = 7 femto Coulombs





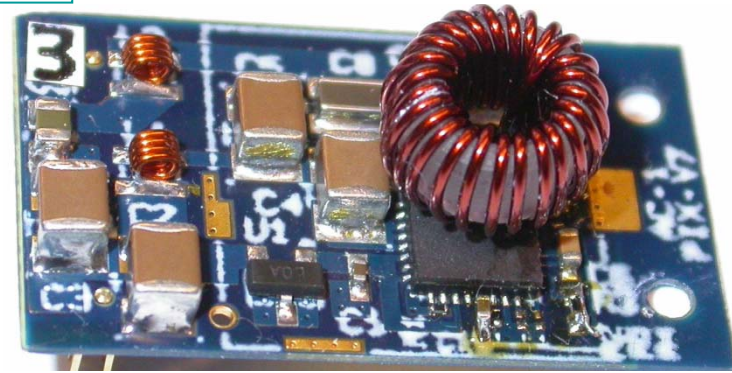
## Converters with Toroid

Size 28.5 mm x 13.5 mm x 10 mm height



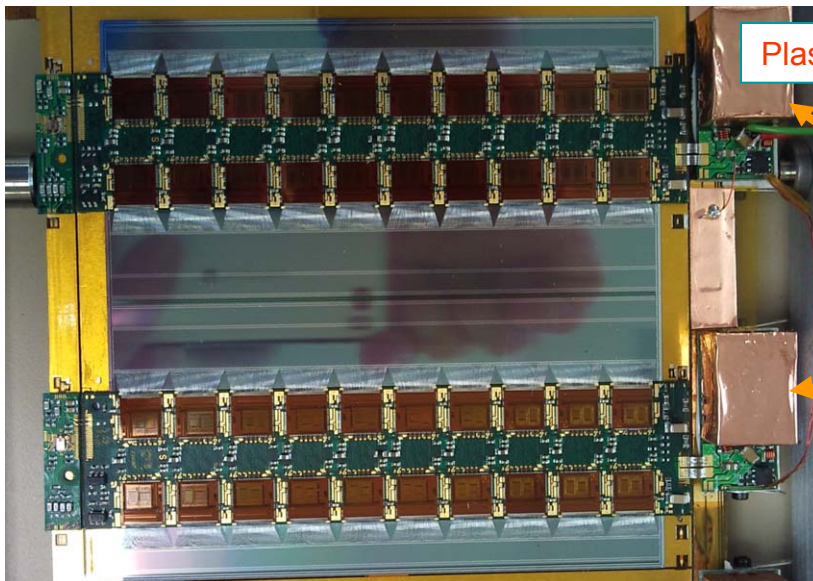
F. Faccio: Development of DCDC converters @ CERN

<http://project-dcdc.web.cern.ch/project-DCDC/public/Documents/SM01C%20Datasheet.pdf>

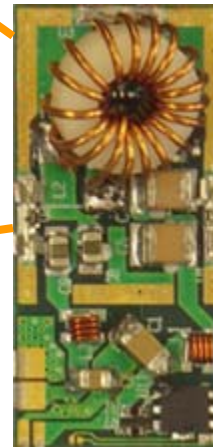


Katja Klein: DC-DC Converter Development for the CMS Pixel Upgrade

<https://indico.cern.ch/conferenceDisplay.py?confId=127662>



Plastic Box with Cu Tape for Shielding



Air Core Toroid: OD = 10 mm, ID = 4 mm  
thickness = 4 mm, # of turns = 20

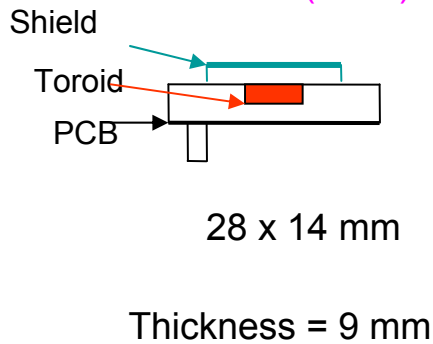
ATLAS Stavelet Update: Upgrade- Peter Phillips

TWEPP 2012 Topical Workshop on Electronics for Particle Physics. 17-21 September 2012 Oxford University, UK

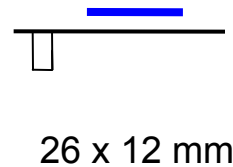


# Form Factor Comparison Toroid vs 2D Inductor Spirals

CERN (2012)

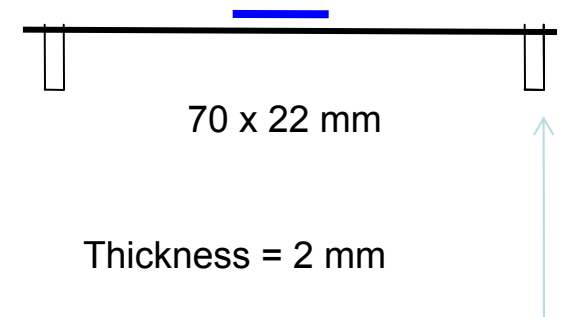


Yale Proposed (2012)



Thickness = 1.6 mm

Yale Model 2151 (2009)



Thickness = 2 mm

Connector

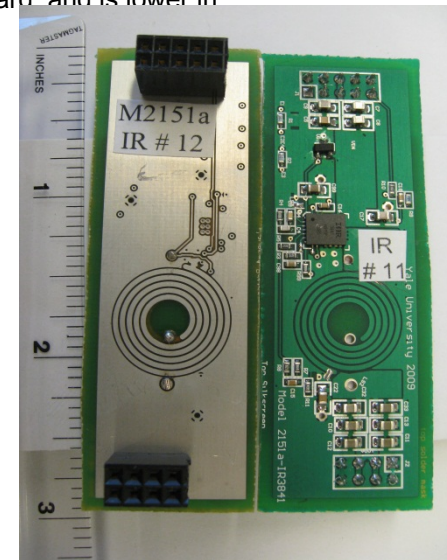
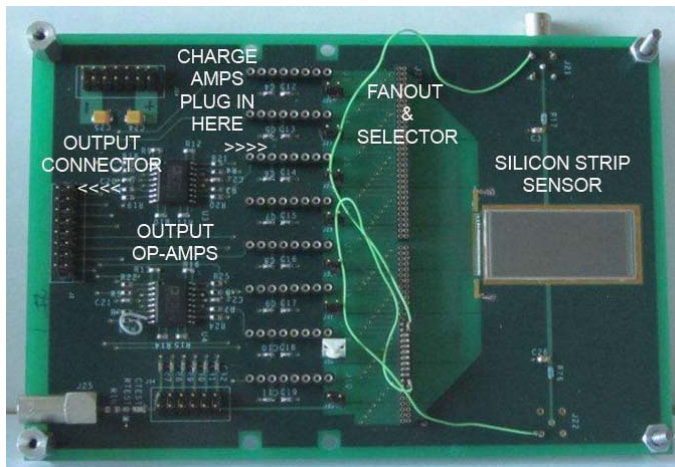
Thickness excludes power connector

# Noise Toroid with shield vs unshielded 2D Inductor

We have used a working 64 channel baby GLAST Silicon strip detector in the lab to measure noise pickup from DC-DC converters. This test board was designed by David Lynn at BNL. The detector strip pitch is 228  $\mu\text{m}$ , size is 15 mm x 35 mm, with substrate thickness of 410  $\mu\text{m}$ . The strips are wire bonded on the PCB and fanned out to high density connectors where 8 channels can be selected for readout by 8 charge sensitive preamps (Cremat CR110, gain 1.4 V/pC) followed by a 10x voltage gain op-amp output driver. In this setup a minimum ionizing particle signal is estimated to be about 32 mv.

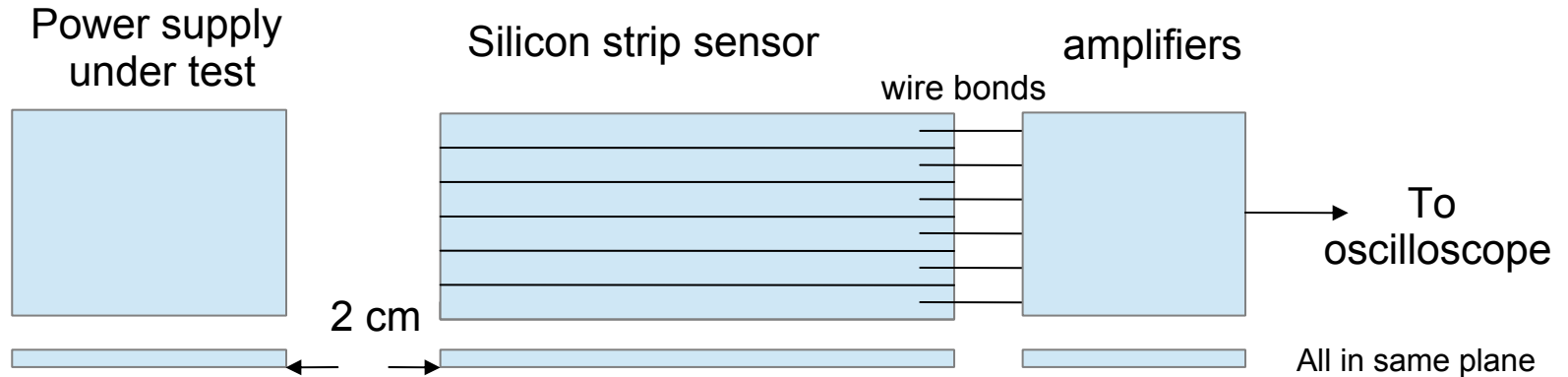
The analog output signals are measured with an oscilloscope. The advantage of this analog readout instead of the digital readout used at Liverpool is that with the oscilloscope we can easily see the switching frequency noise, even when buried in other noise sources. In addition, the waveform can be Fourier analyzed to accurately measure the noise at the DC-DC switching frequency and its harmonics.

In the tests at Yale the DC-DC was placed in the same plane as the Silicon strip detector and about 1 - 2 cm from the end of the detector [fig. 7]. We have measured noise with a sample of the CERN type DC-DC with a shielded toroidal inductor [ref. 5] and a Yale designed DC-DC with an unshielded flat spiral inductor. The noise from the toroid DC-DC was about 4 mv p-p without the copper shield, and about 1 mv p-p with the shield. The Yale DC-DC also measured 1 mv p-p noise. The Yale DC-DC has about the same footprint as the toroid DC-DC excluding the power connectors, but is much thinner, barely thicker than the pc board and is lower in mass.



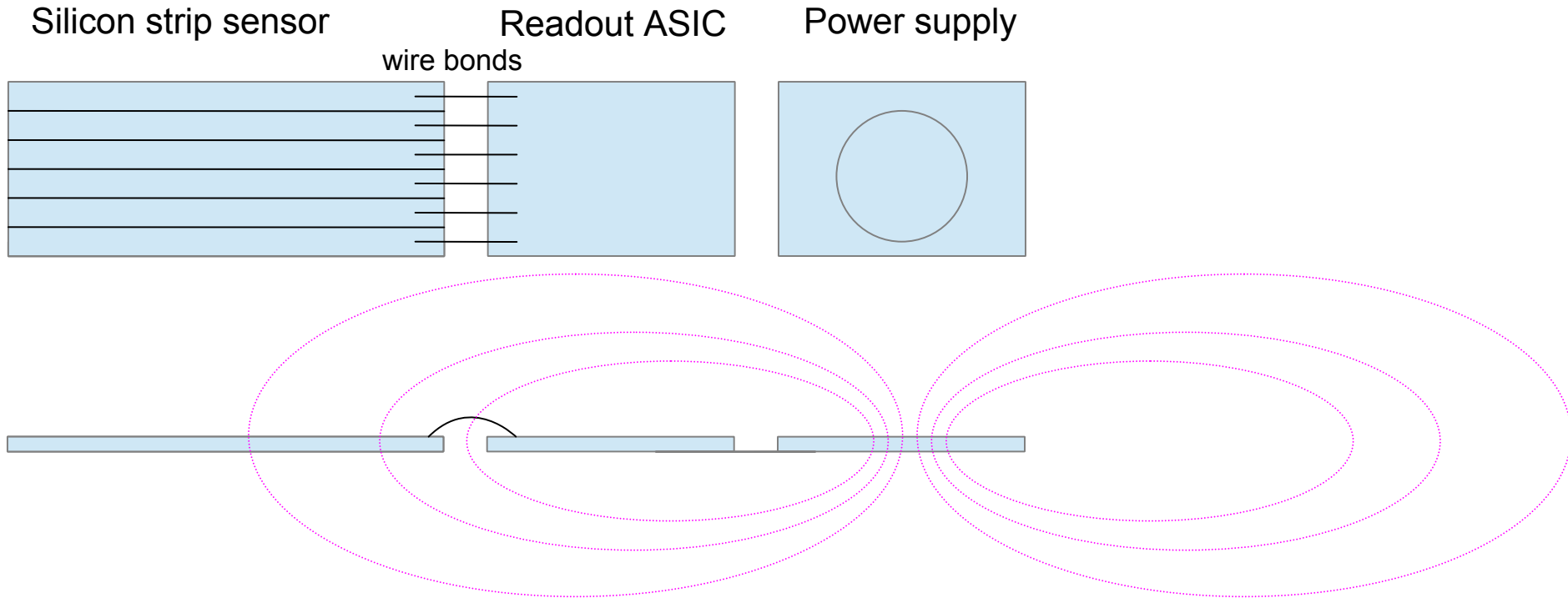
*Test Board designed by David Lynn (BNL)  
Built by Chris Musso (NYU)  
with GLAST Silicon Strip Detector & Analog Readout*

# Radiated Noise test with silicon sensor at Yale



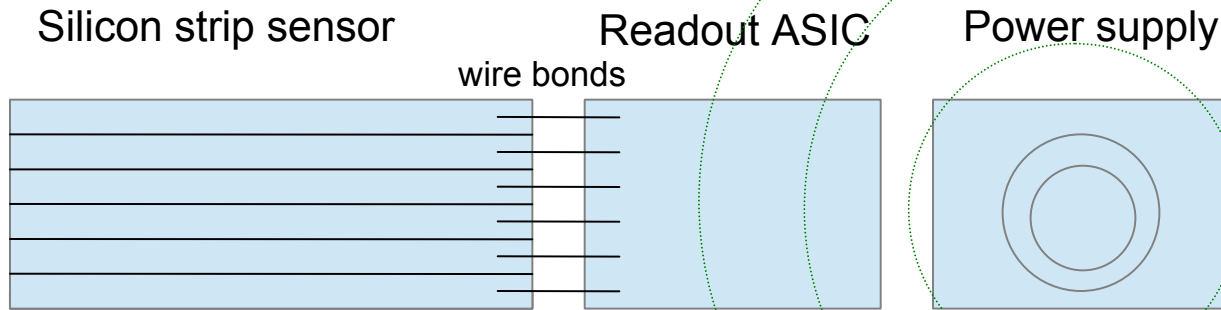
Noise measured with oscilloscope	
Power supply with unshielded 3-D toriodal inductor	4 mv peak to peak
Power supply with shielded 3-D toriodal inductor	1 mv peak to peak
Power supply with unshielded 2-D flat spiral inductor	1 mv peak to peak

# 2-D flat coil magnetic field



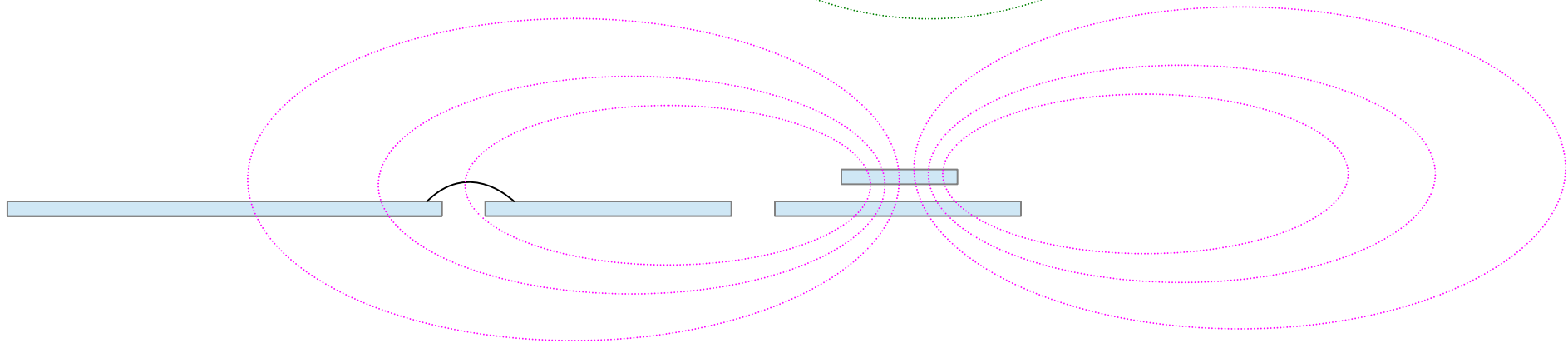
Magnetic field lines passing through sensor and wire bonds are **perpendicular to the plane** and will not induce noise in the sensor or in the wire bonds.

# 3-D Toroid coil magnetic field



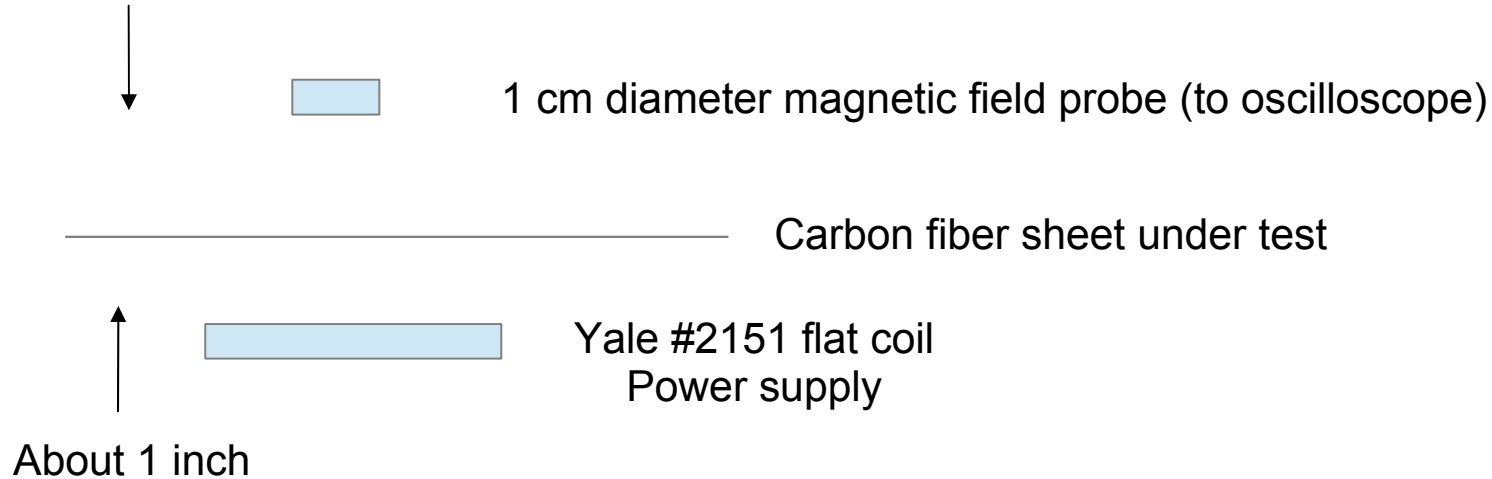
Leakage from toroid is **parallel to the plane of sensor**  
and will induce noise in the sensor

**These effects require shielding the toroid**



The single turn effect of the toroid produces the same field as the flat spiral  
But it is **not perpendicular** to the plane as it crosses the sensor  
since the toroid is above the plane

# Carbon Fiber shielding tests

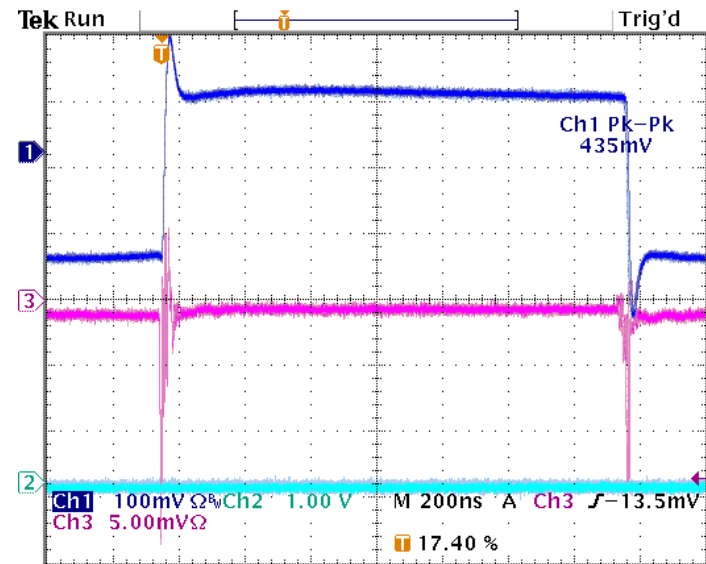


Result with no carbon fiber sheet

Switching frequency less than 500 KHz

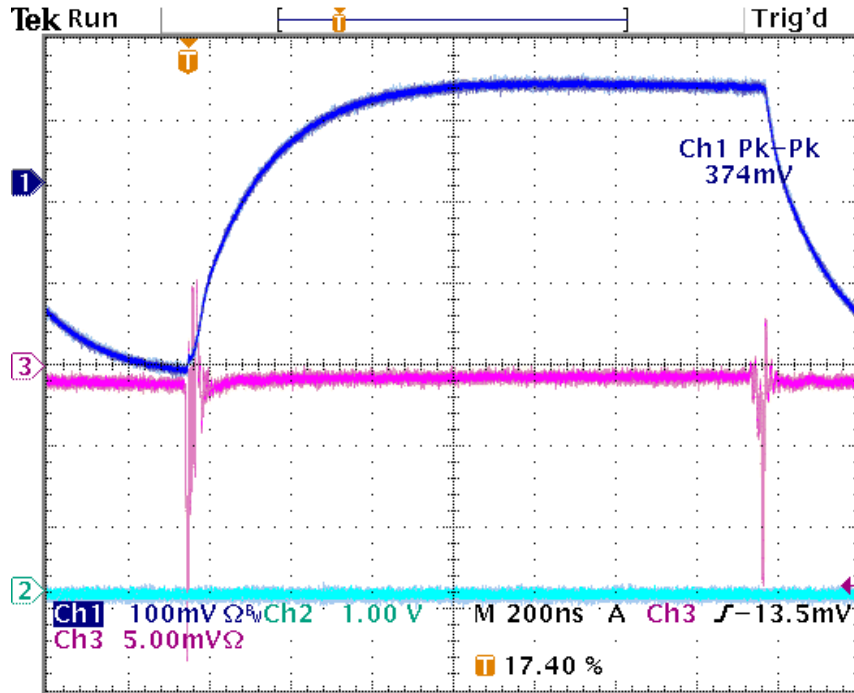
Blue trace is probe

Red trace is scope trigger

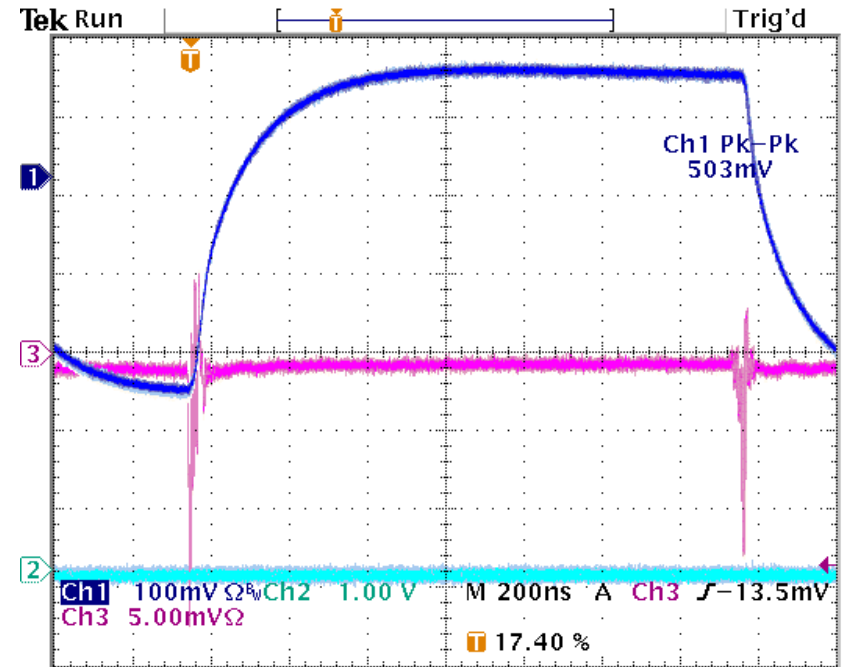




# Carbon Fiber shielding tests



6 layer carbon fiber sample from Fermilab  
Rise time about 200 nS



3 layer carbon fiber sample from LBL  
Rise time about 100 nS

Al foil results in complete shielding (not shown, very dull picture).  
Both Carbon fiber sheets shield only high frequencies components.

Can be used as an EMI Shield ?

# Summary

- ❖ Reduce Power Losses to deliver more Power
- ❖ Look out for Commercial Converters with Thin Gate Oxide
- ❖ GaN for High frequency & Efficiency. Future with integrated GaN Driver
- ❖ 2D inductors are superior
- ❖ Powering detectors : Standard ~400 DC > Isolated 48 V into detector
- ❖ Carbon Fiber for shielding is promising

Working on Physics Power Supply  
Is not considered a Cool thing to do!



Thanks for your Attention

Top of the World is Cool but lonely !  
Let us keep it cool with highly efficient PS

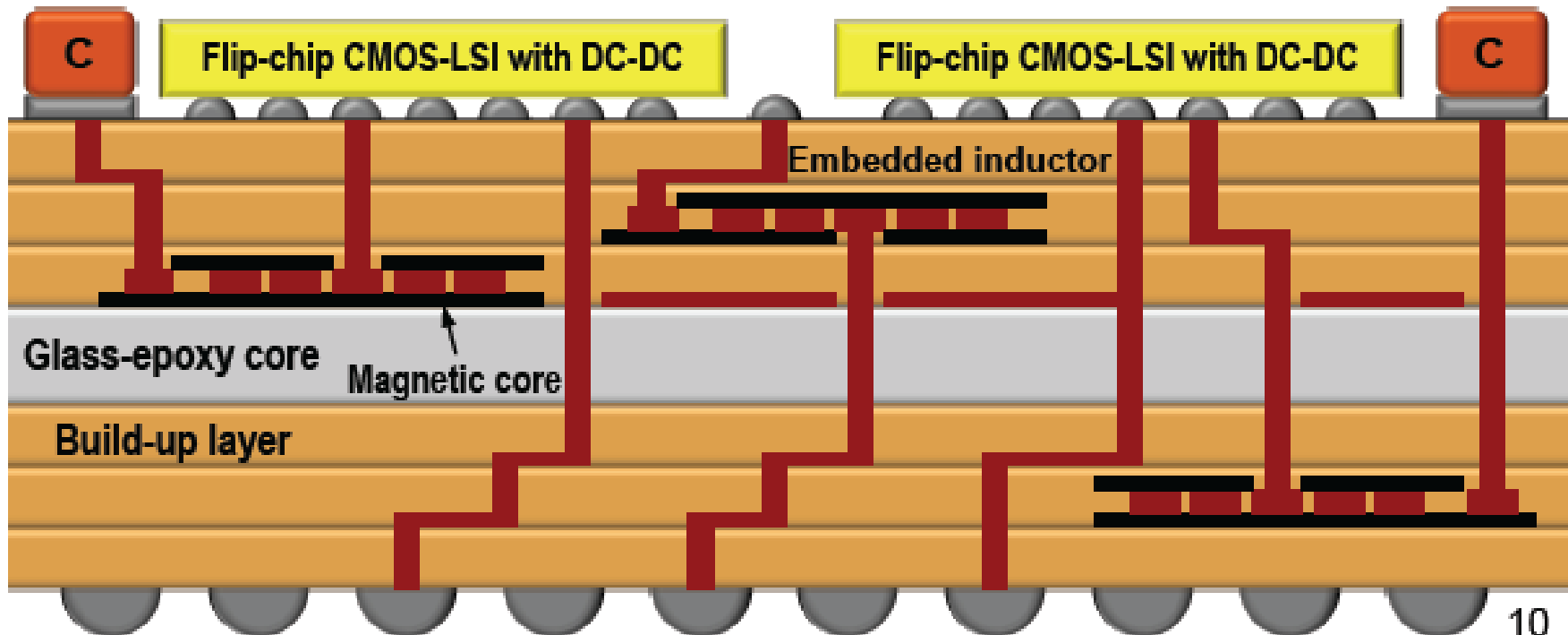
# Back up Slides

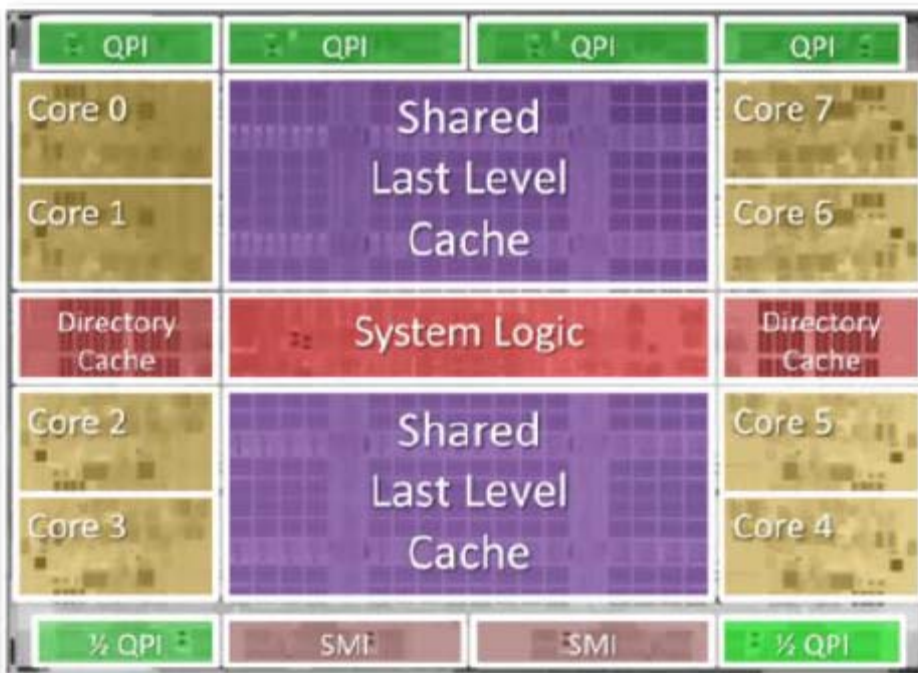
## □ Objective ; Package-level power grid (PLPG)

Power magnetics embedded in package

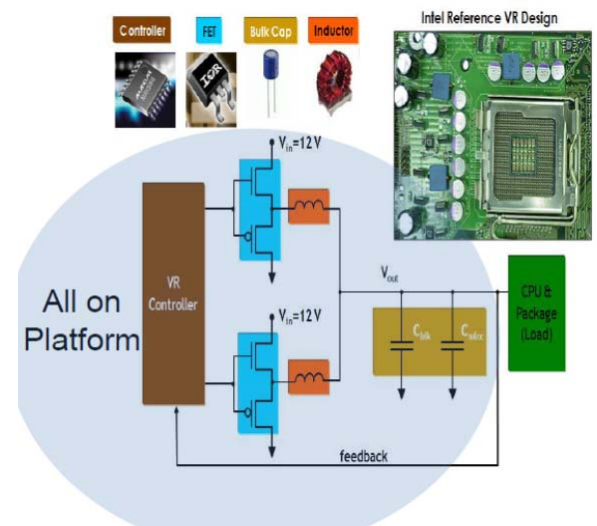
**Embedded power inductor in package**

Low cost, Low profile ; tens micron height, Small near-EMI ; magnetic core

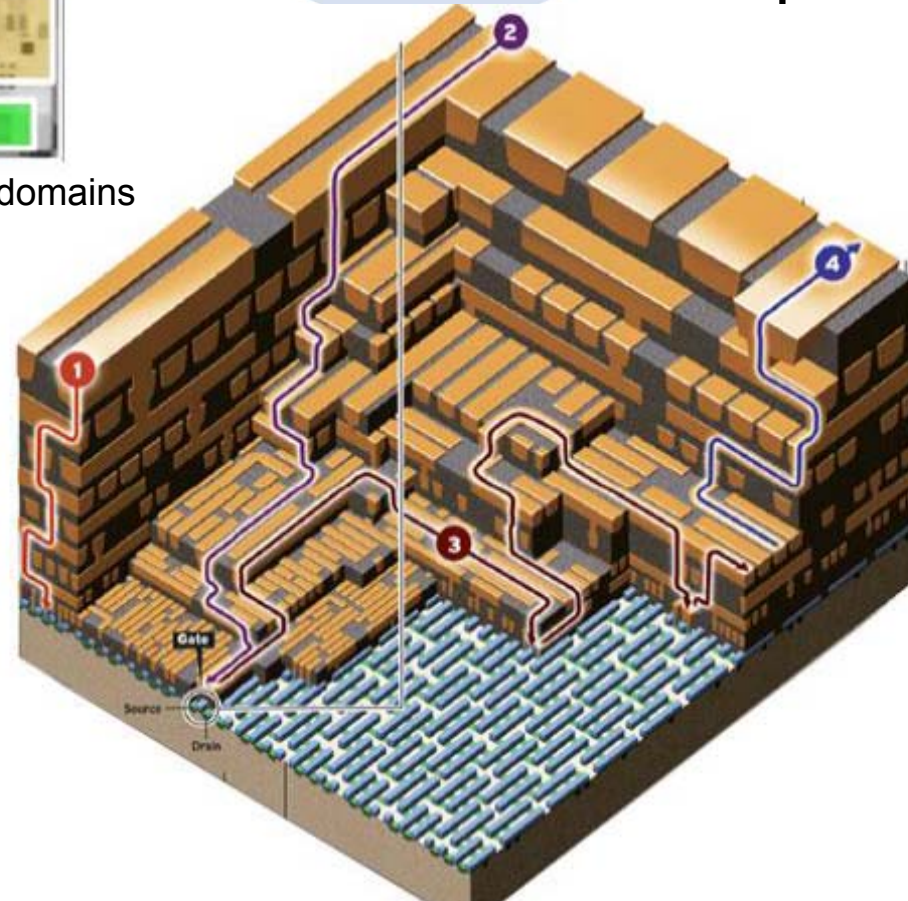




8 Core Intel PSN IPF Microprocessor with 10+ Voltage domains



Creation of test benches & tools to project and understand impact of degraded power delivery in **pre-Si**



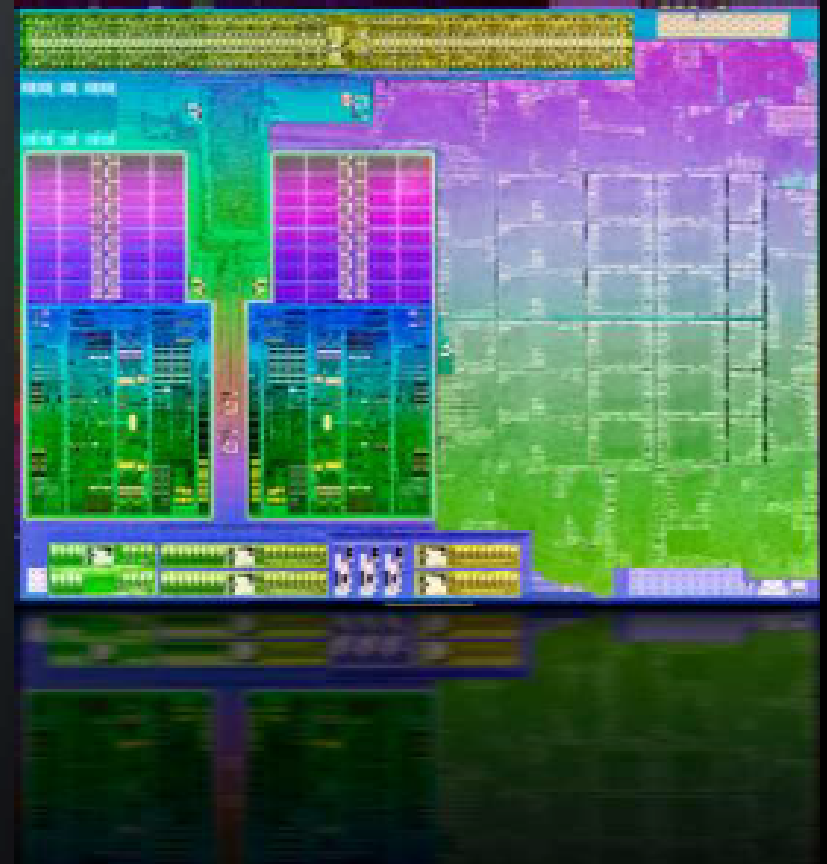
Era of Intelligent Power Delivery  
 Mandy Pant & Bill Bowhill  
 PWRSoC 2012



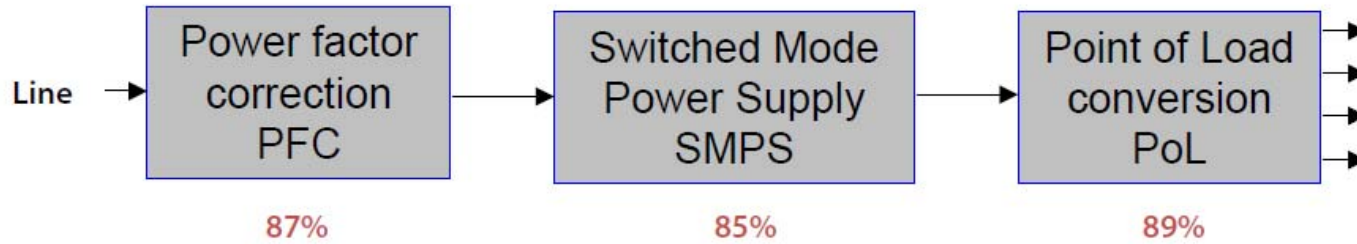
# HIGH PERFORMANCE APU "TRINITY"

- "Piledriver" Cores
  - Quad CPU Core with total of 4MB L2
- 2nd-Gen AMD Radeon™ with DirectX® 11 support
  - 384 Radeon™ Cores 2.0
- HD Media Accelerator
  - Accelerates and improves HD playback
  - Accelerates media conversion
- Enhanced Display Support
  - 3 Simultaneous DisplayPort 1.2 or HDMI/DVI links
  - Up to 4 display heads with display multi-streaming

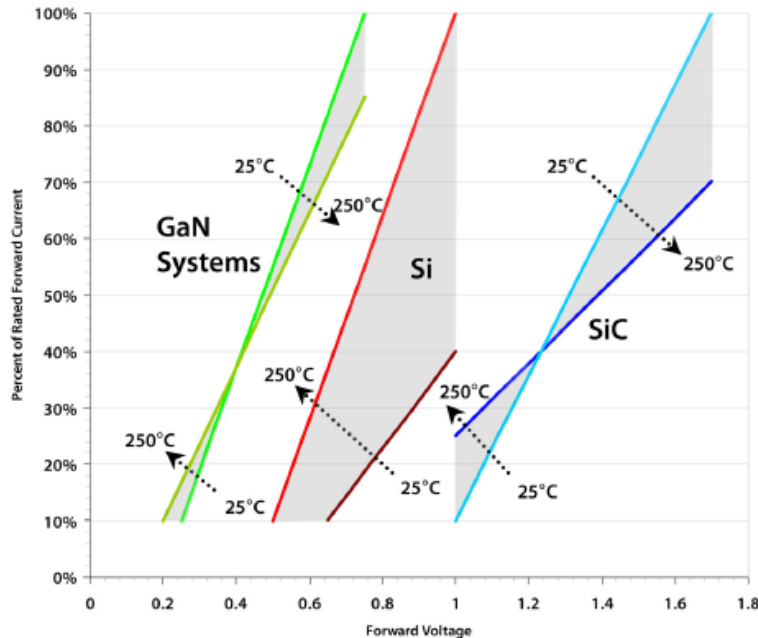
	Nominal Voltage (V)	TDC (A)	Max Load Step (A)
VDD	Variable	50	42
VDDNB	Variable	29	37
VDDIO	1.5	3.2	-
VDDR	1.2	3.5	-
VDDP	1.2	4	-
VDDA	2.5	0.75	-



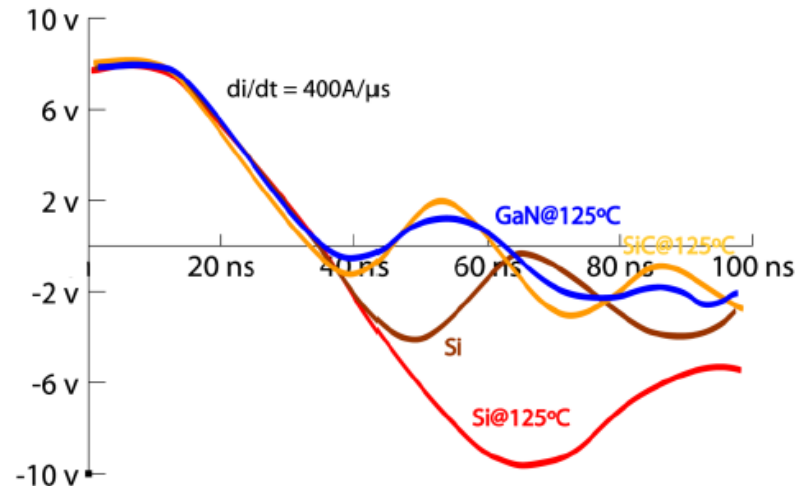
← 6 voltage rails



Typical conversion efficiency today

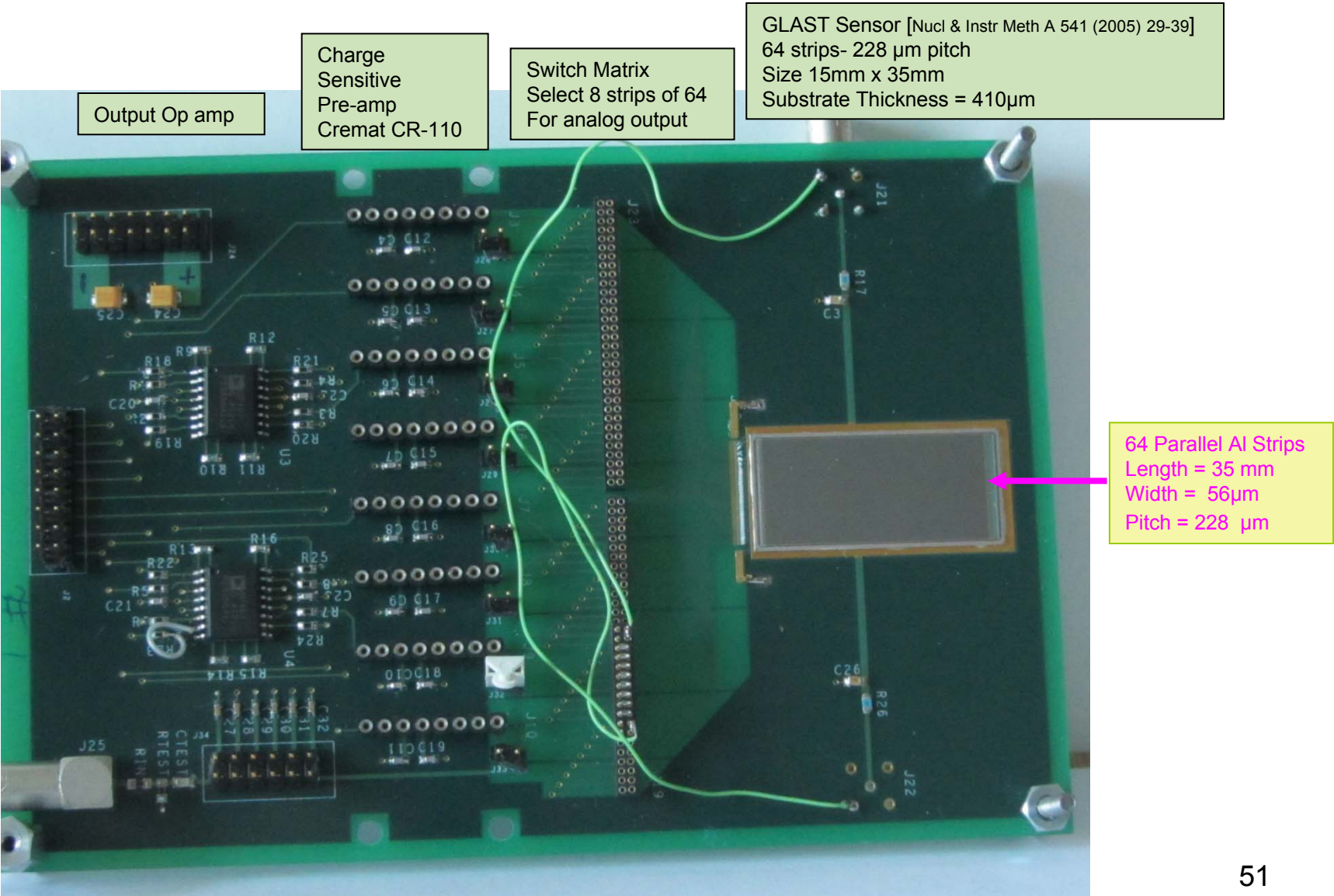


- Ultra Low Voltage Drop
- Temperature Stable

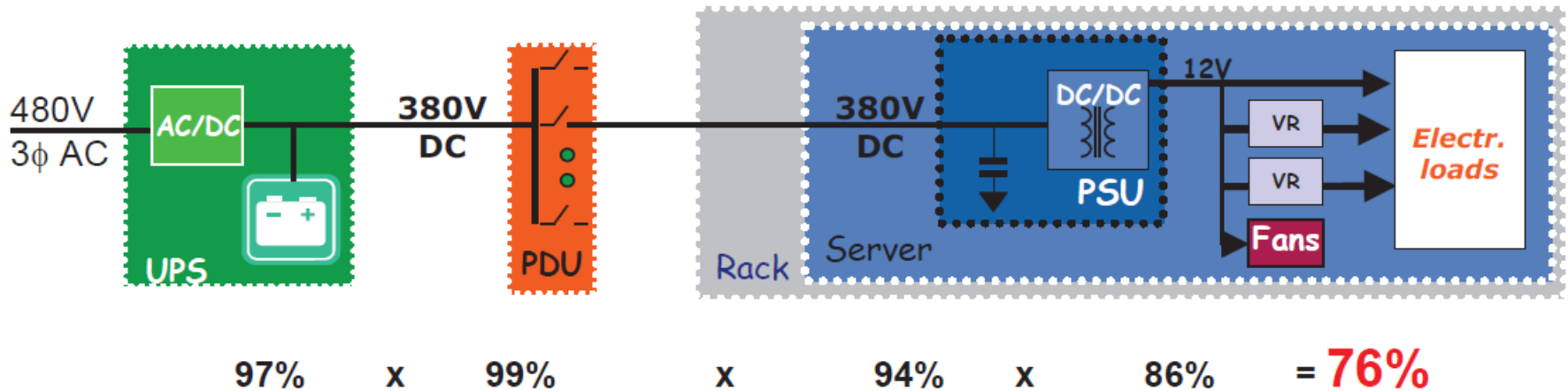
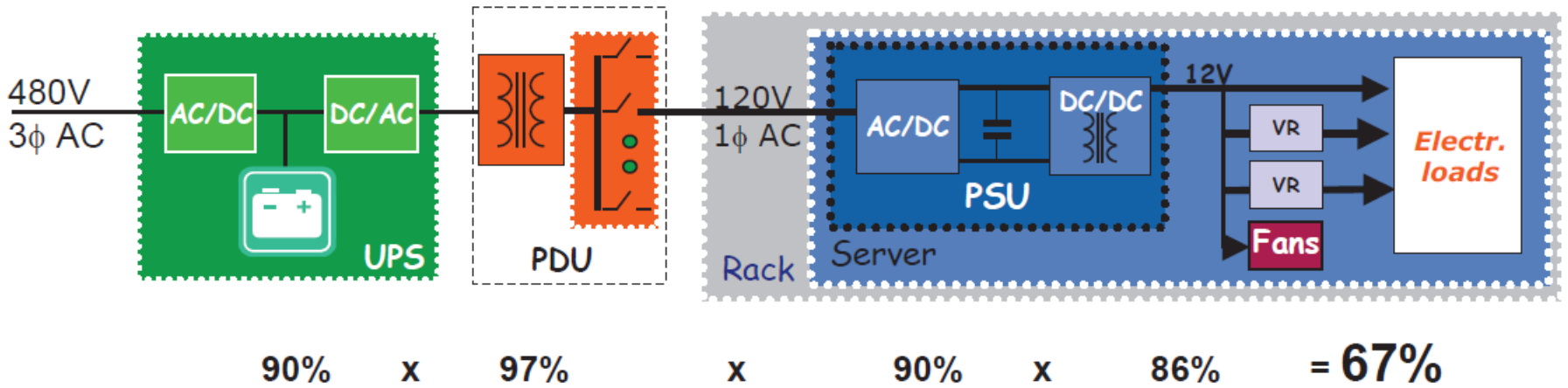


- Zero charge storage
- Temperature Stable

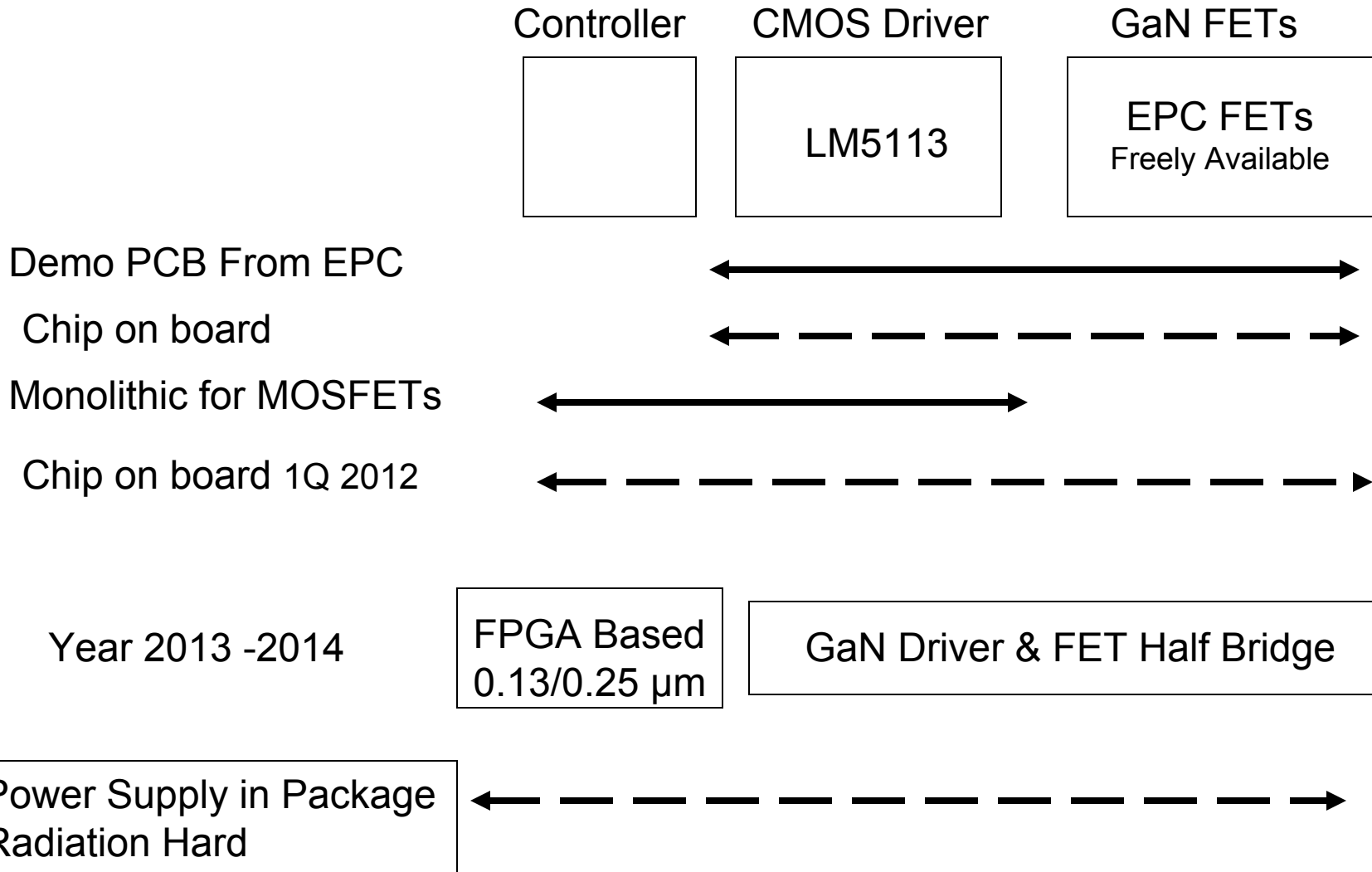
# Test Silicon Strip Detector



# Efficiency Improvement with DC 380 Volts



# Market Trend





# Wireless Power

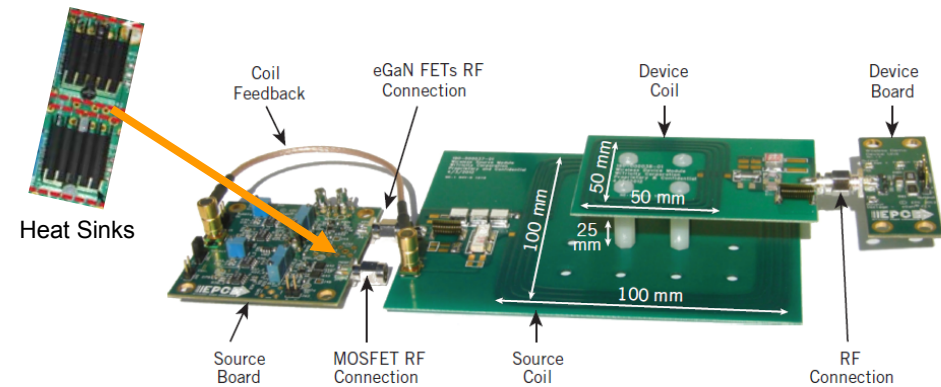
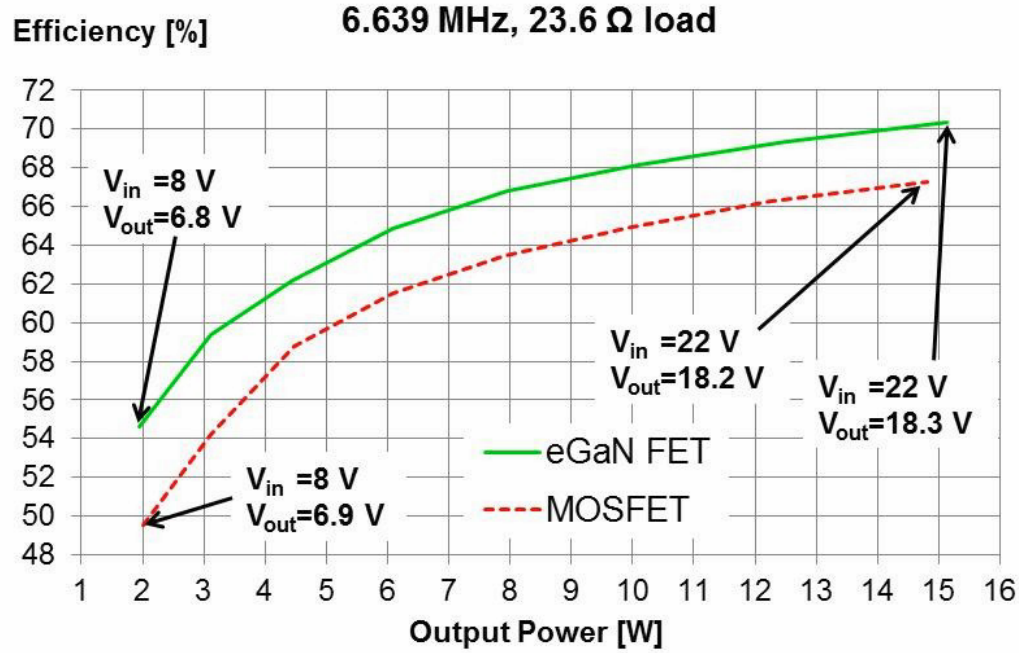
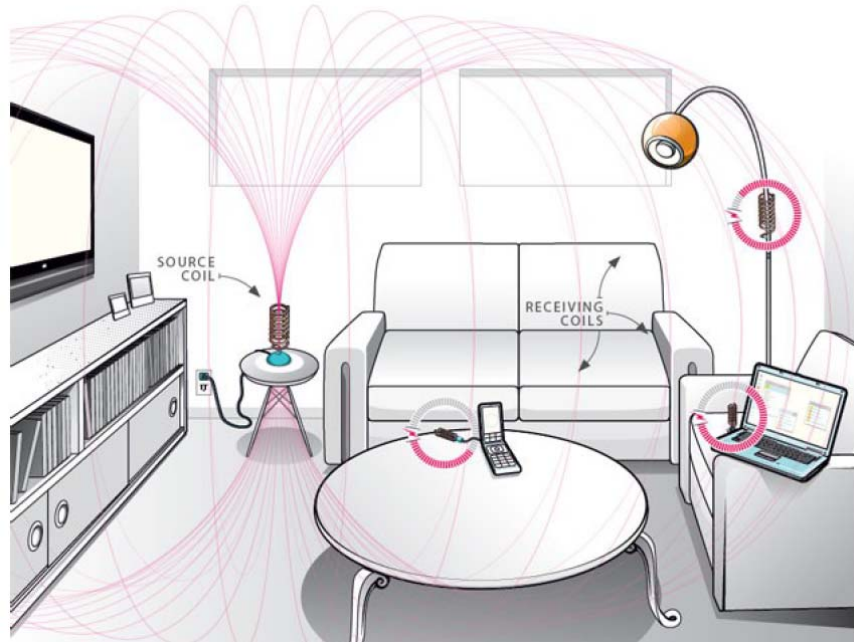
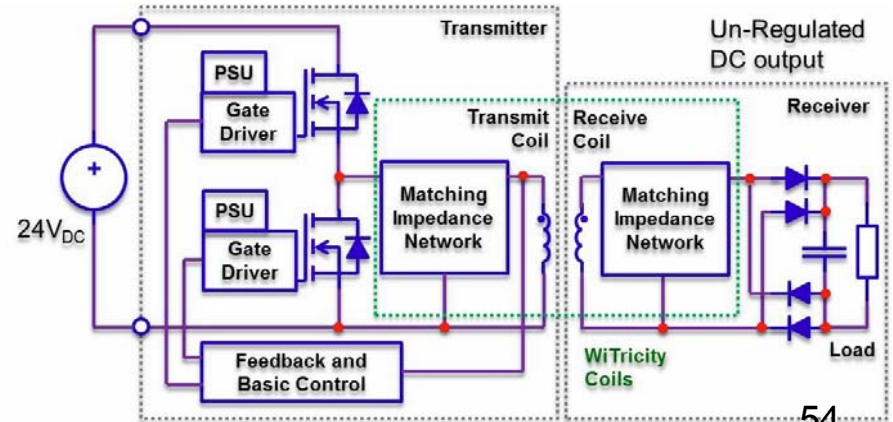
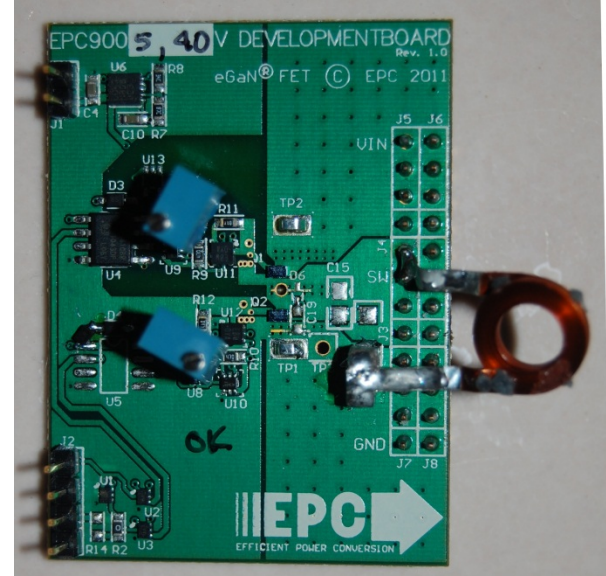
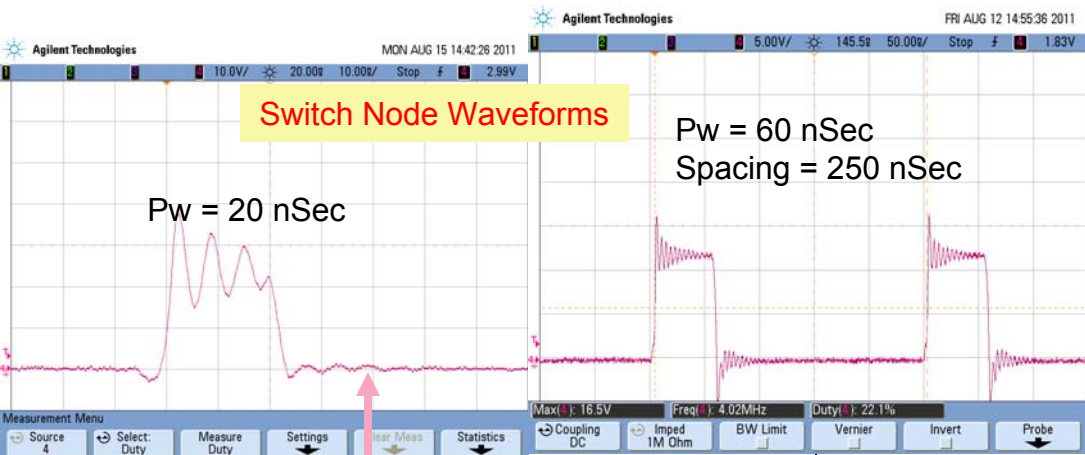


Fig. 3. Wireless energy system setup, with 50Ω SMA connectors used to interconnect each board. Boards were co-developed by EPC and WiTricity.

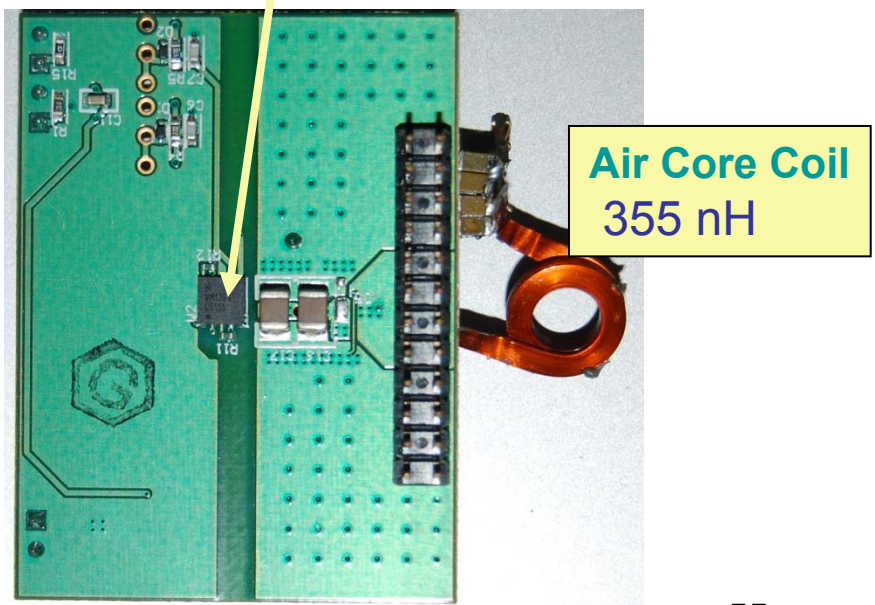
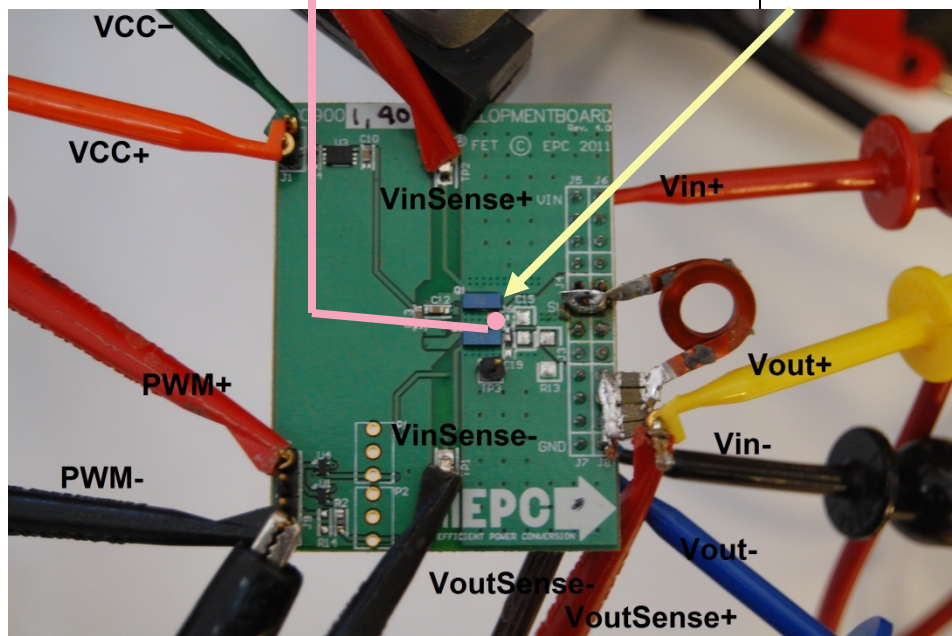




# eGaN with discrete & LM5113 Driver



National eGaN Driver LM5113 on Bottom  
eGaN on Top side



Aircoil EPCOS-B82559A0392A013 3.9  $\mu$ H / 355 nH without Ferrite. 5 m $\Omega$

# Three Foundries with Thin Oxide LDMOS Process Non IB

Company	Device	Process	Foundry	Oxide	Time in	Dose before	Observation
		Name/ Number	Name	Thickness	Seconds	Damage seen	Damage Mode
			Country	nm			
IHP	ASIC custom	SG25V GOD	IHP, Germany	5		53 Mrad	slight damage
XySemi	FET 2 amps	HVMOS20080720	China	7		52 Mrad	minimal damage
XySemi	XP2201	HVMOS20080720	China	7			In Development
XySemi	XPxxxx	HVMOS20080720	China	7			In Development Synch Buck
XySemi	XP5062		China	12.3	800	44 krad	loss of $V_{out}$ regulation
TI	TPS54620	LBC5 0.35 $\mu$ m		20	420	23 krad	abrupt failure
IR	IR3841			9 & 25	230	13 Krads	loss of $V_{out}$ regulation
Enpirion	EN5365	CMOS 0.25 $\mu$ m	Dongbu HiTek, Korea	5	11,500	85 krad	Increasing Input Current,
Enpirion	EN5382	CMOS 0.25 $\mu$ m	Dongbu HiTek, Korea	5	2000	111 Krads	loss of $V_{out}$ regulation
Enpirion	EN5360 #2	SG25V (IHP)	IHP, Germany	5	22 Days	100 Mrads	Minimal Damage
Enpirion	EN5360 #3	SG25V (IHP)	IHP, Germany	5	10 Days	48 Mrads	Minimal Damage

# Signal Chain

